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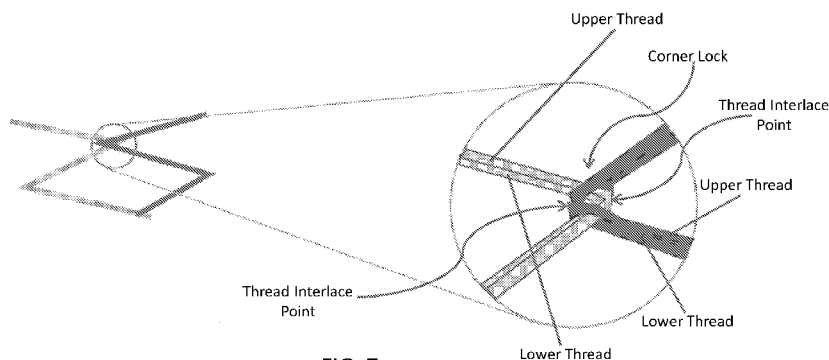


FIG. 7

(57) **Abstract:** Stitching patterns overlap to produce a corner-locked stitch pattern. The corner-locked stitch pattern includes one or more thread interlace points, and one or more overlays of threads from overlapping patterns. A network of corner-lock stitch patterns produces a mesh, which may be embroidered into a substrate, such as a medical textile or biotextile. Corner-lock stitch patterns resist puncture-induced and tension-induced deformation of mesh pores between corner-locked stitch patterns, and may be used to modulate compliance and enhance strength properties of a substrate into which they are sewn.

CORNER-LOCK STITCH PATTERNS

CROSS REFERENCE TO RELATED APPLICATIONS

This application claims priority to U.S. Provisional Application No. 62/186,437 filed on June 30, 2015, the contents of which are incorporated by reference herein, in their entirety and for all purposes.

FIELD

The disclosure relates generally to the field of sewing. More particularly, the disclosure relates to corner-lock stitches made by overlaying threads of separately laid stitch patterns, with the overlays being supported by thread interlace points near to the overlay points. The disclosure further relates to methods for producing these corner-lock stitches, meshes formed from a plurality of interwoven corner-lock stitches, and substrate materials, including substrate meshes, comprising corner-lock stitch patterns. The corner-lock stitches resist deformation, stretching, and pulling apart of the stitch patterns. The corner-lock stitches can be used to modulate the compliance of a substrate, and can also be used to enhance the strength of a substrate.

BACKGROUND

Various publications, including patents, published applications, technical articles and scholarly articles are cited throughout the specification. Each of these cited publications is incorporated by reference herein, in its entirety and for all purposes.

Sewing is an ancient art, primarily used to join pieces of fabric or like materials together. Sewing may also be used to add designs onto (*e.g.*, embroidery), or reinforce or add strength or rigidity to fabrics or like materials. Yarns or threads bridge pieces of materials together or form the design or reinforcing backbone in the materials.

Yarns or threads are placed via stitching, and stitching may be done by hand or by a machine. Various stitching techniques and patterns are available, depending on the particular application or the type of material.

The advent of the sewing machine introduced the lockstitch (Fig. 1A), whereby two separate threads (or yarns), an upper thread and lower thread, become intertwined by the coordination of the sewing needle, which delivers the upper thread into the material being sewn, and a secondary mechanism, typically a bobbin and bobbin driver, which provides the lower thread. The coordinated movement of the sewing needle and bobbin driver intertwines the upper and lower threads, which is known as a lockstitch, in the material being sewn.

Nearly any material that can be punctured with a sewing needle may be sewn. The materials may be woven, knitted, or non-woven. Historically, such materials included fabrics and textiles. In more recent times, materials have been expanded to include polymeric fabrics, as well as biotextiles and medical textiles. Biotextiles include implantable materials, including extracellular matrix scaffolds, prosthetic heart valves, synthetic skin, and other materials that include living tissue or materials derived from living tissue.

In some biotextiles, a reinforcing mesh may be sewn into the material. Medical practitioners have raised concerns, however, that in the event the biologic substrate material of the biotextiles is destroyed by the body, or resorbs too quickly (*i.e.*, before the body self-repairs the injury for which the biotextile has been implanted), the wide voids/pores/interstices between stitch patterns in the extant reinforcing mesh may stretch open (Fig. 2), and allow body tissue to herniate through the stretched mesh cells, causing a potential serious condition in the patient. Accordingly, there is a need in the art to be able to prevent stretching and deformation of the pores of a sewn mesh, particularly for biotextiles.

SUMMARY

The disclosure features corner-lock stitch patterns, substrates comprising corner-lock stitch patterns, and methods for producing corner-lock stitch patterns or substrates comprising corner-lock stitch patterns. In some aspects, a corner-lock stitch pattern comprises a first pattern of a first upper thread and a first lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread and a second lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles. Yarn may

be used in place of thread in the first pattern, second pattern, or both. At least one of the one or more curves or the one or more angles of the second pattern overlap at least one of the one or more curves or the one or more angles of the first pattern. One or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays in which the second upper thread and second lower thread envelope the first upper thread and first lower thread. In preferred aspects, one or more of the overlaps comprises a corner-lock stitch pattern comprising two thread interlace points and two thread overlays in which the second upper thread and second lower thread envelope the first upper thread and first lower thread.

In some aspects, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each angle. In some aspects, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points in close proximity to the vertex of each angle. In some aspects, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of each angle. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

The first pattern may comprises a plurality of angles forming one or more polygonal rings. The second pattern may comprise a plurality of angles forming one or more polygonal rings. At least one ring of the second pattern may overlap at least one ring of the first pattern, and each overlapping ring preferably comprises a corner-lock stitch pattern. The corner-lock stitch pattern may comprise one or more thread interlace points, which thread interlace points may be proximal to the vertex of overlapped angles from each overlapped ring, or may be in close proximity to the vertex of overlapped angles from each overlapped ring, or may be substantially at the vertex of overlapped angles from each overlapped ring. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex. The one or more polygonal rings may

comprise substantially an irregular shape, or a diamond, square, rhomboid, rectangular, or parallelogram shape, or any combination thereof.

In some aspects, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each curve. In some aspects, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points in close proximity to the vertex of each curve. In some aspects, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of each curve. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

The first pattern may comprise a plurality of curves forming one or more circular rings. The second pattern may comprise a plurality of curves forming one or more circular rings. At least one ring of the second pattern may overlap at least one ring of the first pattern, and each overlapping ring preferably comprises a corner-lock stitch pattern. The corner-lock stitch pattern may comprise a thread interlace point, which thread interlace point may be proximal to the vertex of the overlapped curve of each ring, or may be in close proximity to proximal to the vertex of the overlapped curve of each ring, or may be substantially at the vertex of the overlapped curve of each ring. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

Meshes comprising one or more corner-lock stitch patterns are provided. A plurality of corner-lock stitches together form a mesh.

Substrate materials comprising one or more corner-lock stitch patterns are provided. A corner-lock stitch pattern, or mesh thereof, is sewn or embroidered into or onto a substrate. The substrate itself may be a mesh. In some aspects, a substrate comprising a corner-lock stitch pattern sewn or embroidered onto or into the substrate comprises a hernia repair

material. The substrate may comprise a polymer. The substrate may comprise a medical textile. The substrate may comprise a biotextile. The thread or yarn used to sew or embroider the corner-lock stitch pattern may comprise a polymer.

In a mesh comprising a plurality of corner-lock stitch patterns, the pores of the mesh, as bound by a plurality of corner-lock stitches, may have a substantially diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof. The pores of the mesh may have substantially a hexagonal shape. The pores of the mesh may have a substantially octagonal shape. The pores of the mesh may have a substantially circular shape. The pores may be arranged in one or more rows, in any directional orientation. The pores may overlap other pores.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, wherein the first pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, wherein the second pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles. Based on such pattern sewing, at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of each curve, angle, or curve and angle, and two thread overlays proximal to each vertex. Each thread overlay comprises the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

In some aspects of the methods, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each angle. In some aspects, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points in close proximity to the vertex of each angle. In some aspects, the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps

comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of each angle. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

The first pattern may comprise a plurality of angles forming one or more polygonal rings. The second pattern may comprise a plurality of angles forming one or more polygonal rings. At least one ring of the second pattern may overlap at least one ring of the first pattern, and each overlapping ring preferably comprises a corner-lock stitch pattern. The corner-lock stitch pattern may comprise one or more thread interlace points, which thread interlace points may be proximal to the vertex of overlapped angles from each overlapped ring, or may be in close proximity to the vertex of overlapped angles from each overlapped ring, or may be substantially at the vertex of overlapped angles from each overlapped ring. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex. The one or more polygonal rings may comprise substantially an irregular shape, or a diamond, square, rhomboid, rectangular, or parallelogram shape, or any combination thereof.

In some aspects of the methods, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each curve. In some aspects, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points in close proximity to the vertex of each curve. In some aspects, the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of each curve. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

The first pattern may comprise a plurality of curves forming one or more circular rings. The second pattern may comprise a plurality of curves forming one or more circular rings. At

least one ring of the second pattern may overlap at least one ring of the first pattern, and each overlapping ring preferably comprises a corner-lock stitch pattern. The corner-lock stitch pattern may comprise a thread interlace point, which thread interlace point may be proximal to the vertex of the overlapped curve of each ring, or may be in close proximity to proximal to the vertex of the overlapped curve of each ring, or may be substantially at the vertex of the overlapped curve of each ring. In any such case, the two or more thread overlays may be proximal to the vertex, or may be in close proximity to the vertex, or may be substantially at the vertex.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, wherein the first pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, wherein the second pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles. Based on such pattern sewing, at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays. Each thread overlay comprises the second upper thread and second lower thread enveloping the first upper thread and first lower thread. In some aspects, the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings. In such patterns, at least one ring of the second pattern overlaps at least one ring of the first pattern, and at least one of the overlapping rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, wherein the first pattern comprises one or more straight lines, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, wherein the second pattern comprises a plurality of angles forming one or more polygonal rings. Based on such sewing patterns, at least one ring of the

second pattern overlaps at least one of the straight lines of the first pattern and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays. Each thread overlay comprises the second upper thread and second lower thread enveloping the first upper thread and first lower thread. In some aspects, at least one of the polygonal rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

Such methods may be used to form a mesh comprising one or more corner-lock stitch patterns. Such methods may be used to impart one or more corner-lock stitch patterns, including a mesh comprising such patterns, into a substrate. The substrate may comprise a polymer. The substrate may comprise a medical textile. The substrate may comprise a biotextile. The thread or yarn used to sew or embroider the corner-lock stitch pattern may comprise a polymer. The mesh and/or substrate material may be biocompatible, and may be resorbable. The mesh and/or substrate material may comprise a hernia repair implant.

BRIEF DESCRIPTION OF THE DRAWINGS

According to common practice, the various features of the drawings are not to scale. On the contrary, the dimensions of the various features are arbitrarily expanded or reduced for clarity. Included in the drawings are the following figures.

Fig. 1A shows an example of a typical lockstitch, having intertwined upper and lower threads. A typical lockstitch as shown may be present in a thread interlace point within a sewing pattern. Fig. 1B shows an example of a stitch pattern in which two straight stitches intersect.

Fig. 2 shows an image of a mesh formed by overlapping straight stitches, where there is no corner-lock at intersecting points. The lack of a corner-lock causes individual pores or clusters of pores within the mesh to stretch and deform. Arrows show examples of such deformations, including widening, narrowing, and mis-shaping of the square/rectangular form originally produced by the overlapping of straight stitch patterns.

Fig. 3 shows an example of a corner-lock stitch pattern. This corner-lock includes a thread interlace point from each thread pattern (shown in the expanded view (circle) as points

A), and two thread overlays (shown in the expanded view as points B). The corner-lock stitch pattern forms a mesh.

Fig. 4A shows an example of another corner-lock stitch pattern in which stitching patterns include a plurality of angles, some of which are formed into polygonal rings (shown for illustration purposes only in a diamond shape). The polygonal rings of separate stitch patterns overlap, establishing the corner-lock within the area of overlap, with the corner-lock including a thread interlace point from each thread pattern and two thread overlays. The corner-lock stitch pattern forms a mesh.

Fig. 4B shows an example of another corner-lock stitch pattern in which stitching patterns include a plurality of angles, some of which are formed into polygonal rings (shown for illustration purposes only in a diamond shape). The polygonal rings of separate stitch patterns overlap, establishing the corner-lock within the area of overlap, with the corner-lock including a thread interlace point from each thread pattern and two thread overlays. The corner-lock stitch pattern forms a mesh.

Fig. 4C shows an example of another corner-lock stitch pattern in which stitching patterns include a plurality of curves, some of which are formed into circular rings. The rings of separate stitch patterns overlap, establishing the corner-lock within the area of overlap, with the corner-lock including a thread interlace point from each thread pattern and two thread overlays. The corner-lock stitch pattern forms a mesh.

Fig. 5A shows an example of another corner-lock stitch pattern in which a stitching pattern of polygonal shapes is overlapped with a straight stitch pattern, establishing the corner-lock within the area of overlap, with the corner-lock including three thread overlays. The corner-lock stitch pattern forms a mesh.

Fig. 5B shows an example of another corner-lock stitch pattern in which a stitching pattern of triangular shapes is overlapped with a straight stitch pattern, establishing the corner-lock within the area of overlap, with the corner-lock including three thread overlays. The corner-lock stitch pattern forms a mesh.

Fig. 5C shows an example of another corner-lock stitch pattern in which a curved

stitched pattern is overlapped with a straight stitch pattern.

Fig. 6 shows an example of the mesh comprising corner-lock stitches placed under lateral tension (*e.g.*, the mesh being pulled in the direction of each arrow). The corner-locked pores do not substantially deform, and the diamond shape is substantially maintained under tension.

Fig. 7 shows a representation of a perspective of a corner-lock stitch, with the lighter grey line illustrating the first stitch pattern and the darker grey line illustrating the second stitch pattern. The expanded view (circle) shows a representation of the configuration of the upper and lower threads at the vertex of the overlapping thread pattern angles. As shown in the expanded view, the upper and lower thread of the second stitch pattern envelope the upper and lower thread of the first stitch pattern near the vertex. As the second stitch pattern is laid, the sewing needle punctures the substrate material adjacent to the vertex of the first stitch pattern, creating a thread interlace point, but the upper and lower threads of the second stitch pattern encircle the upper and lower threads of the first stitch pattern in the process (a first overlay). As the sewing needle moves away to the next puncture point/interlace point in the material along the second stitch pattern, the upper and lower threads of the second stitch pattern again envelope the upper and lower threads of the first stitch pattern (a second overlay). This, in turn, creates the corner lock stitch.

Fig. 8A shows an image of a mesh formed by a corner-locked stitch pattern, including corner-lock stitches at intersecting points. Between intersecting points, the threads are laid in a chain stitch configuration (the threads are looped), for illustration of variable stitching that may be used between corner locks.

Fig. 8B shows an image of a variation of the mesh shown in Fig. 8A. In this variation, a straight stitch is further laid horizontally across each corner-lock.

Fig. 8C shows an image of another variation of the mesh shown in Fig. 8A. In this variation, a second corner-locked stitch pattern is laid on top of the first corner-locked stitch pattern. The second stitch pattern is oriented diagonally relative to the first stitch pattern.

Fig. 9 shows an example of a mesh built upon a corner-lock stitch pattern. The mesh is

shown in a liner X-Y plane. The pores are oriented in a parallelogram-like configuration, laid at about a 45 degree angle.

Fig. 10 shows another example of a mesh built upon a corner-lock stitch pattern. The mesh is shown in a liner X-Y plane. The pores are oriented in a parallelogram-like configuration, laid at about a 55 degree angle.

Fig. 11 shows another example of a mesh built upon a corner-lock stitch pattern. The mesh is shown in a liner X-Y plane. The pores are oriented in a hexagonal, honey-comb-like configuration, laid at about a 61 degree angle.

Fig. 12 shows a representation of puncture forces on a sewn mesh. In part A, a cone (the triangle) is pointed down through the horizontal plane of the mesh (represented by the circle), with the pointed tip of the cone placed in contact with the mesh in an attempt to push the cone through the mesh. Part B represents a non-corner-locked mesh produced by overlapping straight stitches. In part B, the cone is easily pushed into the mesh, causing the threads to spread apart and deform. Part C represents a corner-locked mesh according to this disclosure. In part C, the mesh resists puncture by the cone, and the threads do not spread apart or deform.

Fig. 13 illustrates construction of a stitch pattern (corner-lock stitch, or comparative standard straight grid stitch) onto a substrate. As shown in a cut-away, half view, a substrate comprised of a center of PVA and a perimeter of insoluble polymer is provided, and the desired stitch pattern is sewn into each of the PVA and insoluble polymer. Once the stitch pattern is laid, the PVA center is dissolved away, leaving behind a free mesh in the center.

Fig. 14 shows construction of a stitch pattern onto an Endoform Reconstructive Template (ERT), a biotextile, substrate.

Fig. 15 illustrates how the ball burst test is carried out, with a mesh (with or without an underlying substrate) placed into a clamp, and then with a steel ball forced through the mesh.

Fig. 16 shows the results of a ball burst compliance test on a polyethylene mesh sewn as a corner-lock stitch pattern (dotted line) or a straight stitch pattern (solid line) into a four-layer

ERT substrate. The chart shows force versus displacement.

Fig. 17 shows the results of a ball burst compliance test on a polypropylene mesh sewn as a corner-lock stitch pattern (dotted line) or a straight stitch pattern (solid line), without a substrate. The chart shows force versus displacement.

Fig. 18 shows the results of a ball burst compliance test on a polyethylene mesh sewn as a corner-lock stitch pattern (dotted line) or a straight stitch pattern (solid line), without a substrate. The chart shows force versus displacement.

Fig. 19 shows a bar graph comparing a ball burst strength test carried out using 0.005 inch monofilament thread corner lock or straight stitch patterns, either with a four layer ERT substrate or without a substrate. Peak load (N) was measured.

DETAILED DESCRIPTION

Various terms relating to aspects of the disclosure are used throughout the specification and claims. Such terms are to be given their ordinary meaning in the art, unless otherwise indicated. Other specifically defined terms are to be construed in a manner consistent with the definition provided herein.

As used herein, the singular forms “a,” “an,” and “the” include plural referents unless expressly stated otherwise.

As used herein, the terms “first” and “second” do not necessarily have a temporal relationship. For example, a “second pattern” does not necessarily require that the “second pattern” be sewn after the “first pattern” is sewn. These terms generally include a positional relationship, for example, they may designate that there are two separate patterns that are sewn.

A “thread interlace point” includes a region where a top thread and a bottom thread are intertwined together. This may include, for example, a standard lock stitch (*e.g.*, Fig. 1A). The top and bottom thread may be separate threads, or may be from the same continuous thread. By way of example, but not of limitation, a thread interlace point may be formed where a sewing needle punctures a substrate material or, if the substrate material comprises a mesh,

the thread interlace point may be formed where a sewing needle passes through a pore of the mesh.

A polygon includes shapes comprised of at least angles and vertices, and sides with at least a straight segment at the angle/vertex. The polygon may comprise a regular or irregular shape. A “polygonal ring” comprises a closed polygon.

A “circular ring” includes a closed circle, sphere, oval, ellipse, O-shape, and other shapes comprising rounded sides.

It has been observed in accordance with the disclosure that stitching patterns can be overlaid in a way that produces a locked junction of threads. A plurality of inter-connected corner-locked stitch patterns may be used to produce a mesh. The corner-lock stitches resist puncture and deformation of the mesh (Fig. 12, parts A-C), such that the mesh pores substantially retain their original shape when challenged by a puncture force or by tension in any direction or combination of directions (Fig. 6). A mesh formed from corner-locked stitches may be used as a stand-alone textile resembling a knitted or woven fabric, or may be used as a strengthening, reinforcing, stabilizing, stiffening, or compliance-control pattern sewn or embroidered into or onto a material substrate (*e.g.*, a biotextile, medical textile, or fabric), which substrate material itself may comprise a mesh (*e.g.*, a mesh substrate). Thus, a corner-lock stitch pattern may be used to increase or decrease the level of compliance of, or modulate the directional compliance of a substrate into which the pattern is sewn. A corner-lock stitch pattern may also be used to increase the strength of a substrate into which the pattern is sewn. The mesh and its underlying stitch patterns may be customizable. Accordingly, the disclosure features corner-lock stitch patterns, meshes comprising such stitches, substrates comprising corner-lock stitch patterns or corner-locked meshes, and methods for producing such stitch patterns, meshes, and substrates.

In a first aspect, the disclosure provides methods for producing corner-lock stitches. Corner-lock stitches comprise interlocking stitch patterns. Corner-lock stitches are preferably created by sewing or embroidering, though in some aspects may be created by weaving, knitting, or warp knitting, and other suitable techniques. Sewing may be by machine or by

hand, or by a combination thereof. Sewing may be with a ballpoint needle.

It is highly preferred that the stitching patterns are formed using at least two threads, with one such thread constituting an upper thread and the other thread constituting a lower thread. In some aspects, the stitching patterns may be formed using a single thread, which may be configured in a way to constitute both the upper and lower threads sewn into a pattern. The stitching pattern may be sewn into any configuration, including a regular or irregular, or variable configuration, including combinations or hybrids thereof. It is preferred that corner-lock stitches are produced from continuous sewing, though the corner-lock stitches may be produced from discontinuous sewing. For example, continuous sewing may comprise sewing the first pattern and sewing subsequent patterns without cutting the thread(s). Discontinuous sewing may comprise sewing the first pattern and sewing a subsequent pattern, but cutting the thread(s) at some point before sewing a subsequent pattern, or otherwise between subsequent patterns. In all cases, a yarn or filament may be used in place of thread.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, which first pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, which second pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles. Sewing the second pattern allows at least one of the one or more curves or the one or more angles of the second pattern to overlap at least one of the one or more curves or the one or more angles of the first pattern. One or more such overlaps, in turn, comprise a corner-lock stitch pattern comprising at least one thread interlace point proximal to, in close proximity to, or substantially at the vertex of each curve, angle, or curve and angle, and two thread overlays proximal to, in close proximity to, or substantially at each vertex, and with each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread. An example is illustrated in Fig. 3, Fig. 4A, Fig. 4B, and Fig. 4C. In some aspects, a thread overlay includes the first upper and first lower thread being sandwiched between the second upper thread and the second lower thread (*e.g.*, Fig. 7). A yarn or filament may be used in place of thread.

In some detailed aspects, the first pattern comprises a plurality of curves forming one or more circular rings, and the second pattern comprises a plurality of curves forming one or more circular rings (*e.g.*, Fig. 4C). In such aspects, at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising a thread interlace point proximal to, in close proximity to, or substantially at the vertex of the overlapped curve of each ring and two thread overlays proximal to, in close proximity to, or substantially at each vertex, with each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

In some detailed aspects, the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings (*e.g.*, Fig. 4A and Fig. 4B). In such aspects, at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising at least one thread interlace point proximal to, in close proximity to, or substantially at the vertex of overlapped angles from each ring and two thread overlays proximal to, in close proximity to, or substantially at each vertex, with each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread. More than one interlace point may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten interlace points may be included.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, which first pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, which second pattern comprises one or more curves, one or more angles, or a combination of one or more curves and one or more angles. Sewing the second pattern allows at least one of the one or more curves or the one or more angles of the second pattern to overlap at least one of the one or more curves or the one or more angles of the first pattern. One or more overlaps comprise a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread. *See,*

Fig. 3, Fig. 4A, Fig. 4B, and Fig. 4C. A yarn or filament may be used in place of thread. More than one interlace point may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten interlace points may be included. More than one thread overlay may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten overlays may be included.

In some detailed aspects, the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and at least one of the overlapping rings comprises a corner-lock stitch pattern comprising more than one thread interlace point (*e.g.*, Fig. 4A and Fig. 4B). More than one thread overlay may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten overlays may be included.

In some aspects, the methods comprise sewing a first upper thread and a first lower thread in a first pattern into a substrate material, which first pattern comprises one or more straight lines, then sewing a second upper thread and a second lower thread in a second pattern into the substrate material, which second pattern comprises a plurality of curves or angles forming one or more polygonal rings. Sewing the second pattern allows at least one ring of the second pattern to overlap at least one of the straight lines of the first pattern and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread. A yarn or filament may be used in place of thread. More than one interlace point may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten interlace points may be included. More than one thread overlay may be included, for example, two, three, four, five, six, seven, eight, nine, ten, or more than ten overlays may be included. In some detailed aspects, at least one of the polygonal rings comprises a corner-lock stitch pattern comprising more than one thread interlace point. An example is illustrated in in Fig. 5A, Fig. 5B, and Fig. 5C.

Where polygonal rings or circular rings present, the ring is preferably sewn into the substrate material. In this respect, the ring is affixed to the substrate material, for example, via

standard lockstitches about the ring perimeter and, thus, is distinct from a free-floating thread loop such as a loop stitch.

Corner-lock stitch patterns produced by any of the methods described herein are also provided. Meshes comprising one or more corner-lock stitch patterns produced by any of the methods described herein are also provided (a mesh may include any combination of corner-lock stitch patterns; the mesh need not be homogeneous in terms of the type of its underlying corner-lock stitch pattern). Substrates comprising one or more corner-lock stitch patterns produced by any of the methods described herein are also provided. Substrates comprising a mesh comprising one or more corner-lock stitch patterns produced by any of the methods described herein are also provided

A plurality of corner-lock stitches may be used in combination to create a mesh or a net. Such a mesh or net may be a stand-alone material (e.g., not sewn or embroidered onto or into any other material). In some aspects, the mesh is sewn or embroidered onto or into a substrate. In this respect, the mesh may serve to impart design, strength, stiffness/rigidity, and/or reinforcement into the substrate. In some aspects, the substrate material may be removed or eliminated to leave the mesh as a stand-alone product. For example, the substrate material may be dissolvable, and may be dissolved following sewing or embroidering of the mesh in order to leave the corner-locked mesh behind. The mesh and substrate material may be separated from each other by any suitable technique in order to isolate the mesh.

In any case, the pores of the mesh, being surrounded by corner-locked stitches substantially resist deformation via puncture (Fig. 12, part C), and substantially resist deformation via tension (Fig. 6). By way of example, Fig. 6 shows a representation of a corner-locked mesh, with tension being applied by pulling the mesh in the direction of the arrows. But the corner-lock stitches inhibit substantial widening of the pores in the direction of the tension (as shown in Fig. 6, the tension being applied along a horizontal axis) and inhibit substantial narrowing of the pores in directions other than the direction of the tension (e.g., per Fig. 6, a vertical axis). The corner-locked meshes also resist deformation from vertical tension, or tension from multiple directions, including simultaneous vertical and horizontal tension. This stands in contrast to the deformation caused by puncture or tension as shown in Fig. 12, part B

and in Fig. 2.

A mesh comprises a plurality of pores, or interstices between overlapping threads or yarns, which overlapping threads or yarns may comprise stitched threads or yarns, and which may comprise corner-locked stitches. The corner-lock stitches may surround the pores, being at each corner about the pore shape. The pores may comprise any suitable shape or dimension, or any suitable combination of shapes and/or dimensions. The pores may comprise one or more of a circular or elliptical shape, a square, diamond, parallelogram, or rhomboid shape, a rectangular shape, a triangular shape, a pentagonal shape, a hexagonal shape, a heptagonal shape, an octagonal shape, or other polygonal shape. Non-limiting examples of pore shapes are shown in Fig. 9 (diamond or rhomboid shape), Fig. 10 (square shape), and Fig. 11 (hexagonal shape). The pores may be arranged, for example, in rows, or in a concentric pattern, or in a random pattern. The pores may overlap (*e.g.*, Fig. 11). The pores may be open, or may comprise crossing patterns that span one or more dimensions within the pore (*See, e.g.*, Fig. 8B and 8C). Such crossing patterns may comprise overlapping zigzag stitches, including corner-locked stitches.

The pores may comprise any suitable length, width, or diameter dimensions. Such dimensions may be from about 0.1 mm to about 10 mm. The dimensions may be from about 0.5 mm to about 5 mm, from about 0.5 mm to about 10 mm, from about 1 mm to about 10 mm, from about 1 mm to about 8 mm, from about 1 mm to about 7 mm, from about 1 mm to about 5 mm, from about 1 mm to about 3 mm, from about 1 mm to about 2 mm, from about 3 mm to about 9 mm, from about 3 mm to about 7 mm, from about 3 mm to about 5 mm, from about 4 mm to about 10 mm, from about 4 mm to about 8 mm, from about 4 mm to about 6 mm, from about 5 mm to about 10 mm, from about 6 mm to about 10 mm, from about 7 mm to about 10 mm, from about 8 mm to about 10 mm, or from about 9 mm to about 10 mm.

A corner-lock stitch pattern may be sewn or embroidered into or onto a substrate. The substrate may be any material into which filaments, yarns, or threads may be sewn into a corner-lock stitch pattern according to this disclosure. The substrate may itself comprise a mesh, such that in some aspects, a substrate mesh may comprise a mesh comprising a corner-lock stitch pattern sewn or embroidered into the substrate mesh. A substrate material may be

a natural or synthetic material, may be a textile, and may be woven or non-woven. The substrate or the substrate material may have any thickness, or length and width dimensions. Non-limiting examples of substrate materials include cloth or fabric, lace, leather, silk, linen, nylon, polyester, polypropylene, polyethylene, cotton, satin, wool, bamboo, cashmere, jute, burlap, fleece, felt, spandex, rayon, denim, and other suitable materials, or any combination thereof. In some preferred aspects, the substrate material is a biotextile or a medical textile. Biotextiles or medical textiles may be implantable in or on the human body.

Biotextiles include biocompatible materials, which may be obtained or derived from living tissue. Living tissue includes, for example dermis/skin tissue (and sub-tissue, extracellular matrices), pericardium, peritoneum, intestine, stomach, forestomach, and other suitable tissues. The animal source may be any suitable animal, including a human, pig, cow, or sheep, or may be synthesized, for example, by recombinant expression. Biotextiles may be biodegradable or resorbable. Some non-limiting examples of biotextiles include extracellular matrix-derived tissue scaffolds, autograft tissue, allograft tissue, and xenograft tissue, as well as artificial skin, artificial heart valves, and other implantable prosthetics. Medical textiles include biocompatible materials, which may include synthetic materials. Some non-limiting examples of medical textiles include hernia repair meshes or materials, which may comprise polypropylene, polyethylene, and other implantable prosthetics.

The yarn or threads used to stitch materials and create the substrate, and/or the corner-locked stitches and meshes may be made of any suitable material, and may comprise any suitable weight. The yarn or thread may comprise monofilament yarn or thread, or multifilament yarn or thread. The thread weight may be a function of the purpose to which the corner-locked mesh is used. The thread weight may range from about 20 weight to about 120 weight. The thread may comprise a denier of from about 1 denier to about 2000 denier. The thread may comprise a denier of at least about 20-denier. The thread may comprise a denier of at least about 30-denier. The thread may comprise a denier of at least about 40-denier. The thread may comprise a denier of at least about 50-denier. The thread may comprise a denier of at least about 60-denier. The thread may comprise a denier of at least about 70-denier. The thread may comprise a denier of at least about 80-denier. The thread may comprise a denier of

at least about 90-denier. The thread may comprise a denier of at least about 100-denier. The thread may comprise a denier of at least about 120-denier. The thread may comprise a denier of at least about 150-denier. The thread may comprise a denier of at least about 200-denier. The thread may comprise a denier of at least about 250-denier. The thread may comprise a denier of at least about 300-denier. The thread may comprise a denier of at least about 400-denier. The thread may comprise a denier of at least about 500-denier. The thread may comprise a denier of at least about 600-denier. The thread may comprise a denier of at least about 700-denier.

The yarn may comprise plied yarn or twisted yarn (*e.g.*, z twist or s twist). The thread material may comprise a natural fiber, such as cotton, wool, silk, or other natural material, or may comprise a synthetic fiber such as polyester, nylon, polypropylene, rayon, or other synthetic material. The thread may comprise a continuous filament. The thread may comprise a monofilament. The thread may comprise a staple filament. The thread material may comprise a metal. The thread may comprise a wire, for example, a polymeric wire, composite wire, or metal wire. The thread material preferably is biocompatible and, in some aspects, is resorbable. The thread material may comprise a polydioxanone, polycarbonate, polyurethane, poly(alpha-ester), polyglycolide, polylactide (*e.g.*, poly(L-lactic acid), poly(D-lactic acid), and poly(D,L-lactic acid), poly (4-hydroxybutyric acid) – which is a homopolymer of 4-hydroxybutyrate (4HB), and belongs to a diverse class of materials called polyhydroxyalkanoates (PHAs) – and poly(lactide-co-glycolide)), polycaprolactone, polypropylene, polyester, poly(propylene fumarate), polyanhydride, polyacetal, polycarbonate (*e.g.*, poly(trimethylene carbonate)), poly(ortho ester), polyphosphazene, polyphosphoester, polytetrafluoroethylene, polyethylene terephthalate, or any combination or co-polymer thereof. Polypropylene, polyester, and polyethylene are preferred, with monofilament polyethylene more preferred.

The yarn or thread may be colored. Colors may indicate a proper orientation of the mesh or material + mesh, for example, the colors may indicate the proper orientation for implantation of a hernia repair mesh. Colors may indicate a front or back.

Between corner-locks, the thread may further comprise other stitch patterns, including

a chain stitch, Merrow stitch, lock stitch, zigzag stitch, straight stitch, running stitch, back stitch, satin stitch, or combinations thereof, or any other suitable stitch types. Such patterns may serve, for example, to further strengthen the mesh, or may be decorative.

The following Example is provided to describe corner-lock stitch pattern qualities in greater detail. The Example is intended to illustrate, not to limit.

Example 1

Compliance and Strength of Corner-Lock Stitch Patterns

A corner-lock stitch pattern of polyethylene or polypropylene monofilament threads was embroidered onto a circular substrate comprising a polytetrafluoroethylene (PTFE) external ring (included as a frame, and not to test properties of the stitches sewn into it), and a polyvinyl alcohol (PVA) internal ring (Figure 13). In parallel, a standard straight lock-stitch pattern (*e.g.*, Figure 2, no corner locks) was also embroidered into a PTFE/PVA substrate (Figure 13). Following completion of each type of pattern, the PVA portion of substrate was dissolved away with water, leaving behind an embroidered corner-lock stitch pattern mesh unaffixed to any substrate in the center and also affixed around the perimeter to the insoluble portion of the substrate. Also in parallel, each of corner-lock and comparative straight-lock stitch patterns were embroidered into a four-layer extracellular matrix biotextile substrate, with the substrate not being dissolved away (Figure 14). The test samples are summarized in Table 1 (variables: polypropylene (PP) and high strength polyethylene (PE) monofilaments used for embroidery, with corner-lock or standard straight stitch patterns, on either a 4-layer biotextile substrate or without substrate; Both stitch patterns had a similar pore size of about 3 mm).

Table 1. Test sample arrays

Type	Corner-Lock Mesh	Straight-Lock Mesh	Polypropylene (PP) Monofilament	High-Strength Polyethylene (PE) Monofilament	Substrate – 4 layers	No substrate
A		X	X			X
B		X		X		X
C	X		X			X
D	X			X		X
E		X	X		X	

F		X		X	X	
G	X		X		X	
H	X			X	X	

Each of the stitch patterns (+/ – substrate) were studied for strength and compliance (compliance is a function of, among other things, strength, stress, elongation, rebound, deformability, and elasticity properties of the particular materials or combination of materials) using the Ball Burst test method. The Ball Burst test method is used in the art to measure the force required to rupture a textile, by forcing a 1 inch diameter polished steel ball through a 1.75 inch inner-diameter textile ring at a constant rate of extension, 12 inch/minute (ASTM D767-07 (Reapproved 2011)). The Ball Burst tests were conducted on each stitch pattern (+/ – substrate) on an Instron Model 3345 Single column Tensile Tester with ball burst ring clamps and fixture (Figure 15).

Compliance control tests are charted in Figures 16 through 18. Figure 16 graphs Force (N) vs. Displacement (in mm) data for 2 samples (Type E and G, Table 1), highlighting the compliance difference between the different grid patterns for embroidered tissue. Direction Arrow I shows how, for a given displacement, the corner-lock grid pattern offers less resistance than the standard straight grid pattern. Direction Arrow II shows how, for a given resistance load, the corner-lock stitch patterns allows more ball travel distance than the straight stitch pattern. This illustrates how the corner-lock grid pattern is more compliant than a straight grid pattern, with each pattern made of the same material (high strength PE in Figure 16) and with similar pore dimensions. Figures 17 (PP) and 18 (high strength PE) illustrate this same relationship where the corner-lock stitch pattern and straight stitch pattern were without a substrate samples (Table 1, Type A-D). The data show that the corner-lock stitch pattern is more compliant than the straight-stitch pattern, whether or not a substrate underlies the pattern, and regardless of the stitch pattern thread material. Of note, it was observed that manipulation of the shape and type of the corner-lock stitch patterns allows for modulation (greater or lesser) of the compliance (not shown).

Strength tests are summarized in Figure 19. Figure 19 shows, for the same size

monofilament, the difference between PP and PE materials using averaged Ball Burst peak loads. N-values are either 4 or 6 samples per type. In every paired configuration, the average peak load for the PE was observed to be higher than the average peak load for PP. In the chart, corner-lock versus standard straight stitch patterns, formed of PP or PE, on either a 4-layer biotextile substrate or without a substrate (stitched into PVA that was dissolved away to leave behind the stitch pattern mesh) are compared for their strength. As shown, high strength polyethylene monofilament threads (0.005" monofilament) exhibited higher strength characteristics than polypropylene monofilament threads (0.005" monofilament) in both straight and corner-lock stitch patterns. In general, corner-lock stitch patterns were found to exhibit higher strength characteristics than standard straight stitch patterns.

The disclosure is not limited to the embodiments described and exemplified above, but is capable of variation and modification within the scope of the appended claims.

CLAIMS

We claim:

1. A corner-lock stitch pattern, comprising a first pattern of a first upper thread or yarn and a first lower thread or yarn comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread or yarn and a second lower thread or yarn comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays in which the second upper thread and second lower thread envelope the first upper thread and first lower thread.
2. The corner-lock stitch pattern according to claim 1, wherein the first pattern and the second pattern each comprise one or more angles, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each angle.
3. The corner-lock stitch pattern according to claim 1 or 2, wherein the two or more thread overlays are proximal to the vertex.
4. The corner lock stitch pattern according to any one of claims 1 to 3, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of overlapped angles from each ring and two or more thread overlays proximal to each vertex in which the second upper thread and second lower thread envelope the first upper thread and first lower thread.
5. The corner-lock stitch pattern according to any one of claims 1 to 4, wherein the first pattern and the second pattern each comprise one or more angles, and one or more of the

overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of each angle.

6. The corner-lock stitch pattern according to claim 5, wherein the two or more thread overlays are proximal to the vertex.

7. The corner lock stitch pattern according to claim 5, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising one or more thread interlace points substantially at the vertex of overlapped angles from each ring and two or more thread overlays proximal to each vertex in which the second upper thread and second lower thread envelope the first upper thread and first lower thread.

8. The corner lock stitch pattern according to claim 4 or 7, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

9. The corner lock stitch pattern according to claim 4 or 7, wherein the one or more polygonal rings comprise an irregular shape.

10. The corner-lock stitch pattern according to claim 1, wherein the first pattern and the second pattern each comprise one or more curves, and one or more of the overlaps comprises a corner-lock stitch pattern comprising one or more thread interlace points proximal to the vertex of each curve.

11. The corner-lock stitch pattern according to claim 10, wherein the two or more thread overlays are proximal to the vertex.

12. The corner lock stitch pattern according to claim 10 or 11, wherein the first pattern comprises a plurality of curves forming one or more circular rings, and the second pattern comprises a plurality of curves forming one or more circular rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring

comprises a corner-lock stitch pattern comprising a thread interlace point proximal to the vertex of the overlapped curve of each ring and two thread overlays proximal to each vertex in which the second upper thread and second lower thread envelope the first upper thread and first lower thread.

13. The corner lock stitch pattern according to any one of claims 1 to 12, wherein the first upper thread, the first lower thread, the second upper thread, and the second lower thread comprises a biocompatible material.

14. The corner lock stitch pattern according to claim 13, wherein the biocompatible material is resorbable.

15. The corner lock stitch pattern according to any one of claims 1 to 14, wherein the first upper thread, the first lower thread, the second upper thread, and the second lower thread comprises a monofilament thread.

16. The corner lock stitch pattern according to claim 15, wherein the monofilament thread comprises a monofilament polyethylene thread.

17. A hernia repair material, comprising a substrate comprising the corner-lock stitch pattern according to any one of claims 1 to 16.

18. The hernia repair material according to claim 17, wherein the substrate comprises a polymer mesh.

19. The hernia repair material according to claim 18, wherein the polymer mesh comprises a polymer selected from the group consisting of polydioxanone, polycarbonate, polyurethane, poly(alpha-ester), polyglycolide, poly(L-lactic acid), poly(D-lactic acid), poly(D,L-lactic acid), poly(4-hydroxybutyric acid), polycaprolactone, polyethylene, polypropylene, polyester, poly(propylene fumarate), polyanhydride, polyacetal, polycarbonate, poly(ortho ester), polyphosphazene, polyphosphoester, polytetrafluoroethylene, polyethylene terephthalate.

20. The hernia repair material according to claim 17, wherein the substrate comprises a biotextile comprising an extracellular matrix.

21. A method for sewing a corner-lock stitch pattern, comprising (a) sewing a first upper

thread and a first lower thread in a first pattern into a substrate material, the first pattern comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then (b) sewing a second upper thread and a second lower thread in a second pattern into the substrate material, the second pattern comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of each curve, angle, or curve and angle, and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

22. The method according to claim 21, wherein the first pattern comprises a plurality of curves forming one or more circular rings, and the second pattern comprises a plurality of curves forming one or more circular rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising a thread interlace point substantially at the vertex of the overlapped curve of each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

23. The method according to claim 21, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of overlapped angles from each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

24. The method according to any of claims 21-23, wherein the substrate material comprises a fabric.

25. The method according to any of claims 21-23, wherein the substrate material comprises a biotextile.
26. The method according to any of claims 21-23 or 25, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular matrix.
27. The method according to any of claims 21-23, wherein the substrate material comprises a hernia repair mesh.
28. The method according to any of claims 21-23 or 27, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene.
29. The method according to any of claims 21-28, wherein the substrate material is biocompatible.
30. The method according to any of claims 21-29, wherein the substrate material is resorbable.
31. The method according to any of claims 21-30, wherein the first and second upper and lower threads comprise a biocompatible material.
32. The method according to claim 31, wherein the biocompatible material is resorbable.
33. The method according to any of claims 21-32, wherein at least the first upper and first lower threads are the same continuous thread.
34. The method according to any of claims 21-33, wherein the sewing comprises hand sewing.
35. The method according to any of claims 21-33, wherein the sewing comprises machine sewing.
36. The method according to any of claims 21-35, further comprising, (c) repeating steps (a) and (b) any number of times, thereby producing a mesh comprising a corner-lock stitch pattern within the substrate material.
37. The method according to claim 36, wherein the sewing of steps (a), (b), and (c) is

substantially continuous.

38. The method according to claim 36 or 37, further comprising (d) isolating the mesh from the substrate material.

39. The method according to any of claims 36-38, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

40. The method according to any of claims 36-38, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

41. The method according to any of claims 36-38, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

42. The method according to any of claims 36-38, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

43. The method according to any of claims 36-42, wherein the pores of the mesh are arranged in rows.

44. The method according to any of claims 36-43, wherein at least some of the pores overlap other pores within the mesh.

45. The method according to any of claims 36-44, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

46. The method according to any of claims 36-45, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

47. The method according to any of claims 36-46, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

48. The method according to any of claims 21-47, wherein each upper thread comprises a chain stitch pattern.
49. The method according to any of claims 21-48, wherein each upper thread comprises a yarn.
50. The method according to claim 49, wherein the yarn is a monofilament yarn.
51. The method according to claim 49, wherein the yarn is a multifilament yarn.
52. The method according to any of claims 21-51, wherein the first and second upper and lower threads comprise a continuous filament.
53. The method according to any of claims 21-51, wherein the first and second upper and lower threads comprise a staple filament.
54. The method according to any of claims 21-51, wherein the first and second upper and lower threads comprise a wire.
55. The method according to any of claims 21-54, wherein each upper thread and each lower thread comprises a denier of at least about 20-denier.
56. The method according to any of claims 21-55, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.
57. The method according to any of claims 21-56, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.
58. The method according to any of claims 21-57, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.
59. The method according to claim 23, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.
60. The method according to claim 23, wherein the one or more polygonal rings comprise an irregular shape.
61. A substrate material, comprising a corner-lock stitch pattern produced according to the method of any of claims 21-60.

62. A substrate material, comprising a mesh comprising a corner-lock stitch pattern produced according to the method of any of claims 21-37 or claims 39-60.

63. The substrate material according to claim 62, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

64. The substrate material according to claim 62, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

65. The substrate material according to claim 62, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

66. The substrate material according to claim 62, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

67. The substrate material according to any of claims 62-66, wherein the pores of the mesh are arranged in rows.

68. The substrate material according to any of claims 62-67, wherein at least some of the pores overlap other pores within the mesh.

69. The substrate material according to any of claims 62-68, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

70. The substrate material according to any of claims 62-69, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

71. The substrate material according to any of claims 62-70, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

72. A mesh produced according to the method of claim 38.

73. The mesh according to claim 72, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

74. The mesh according to claim 72, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

75. The mesh according to claim 72, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

76. The mesh according to claim 72, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

77. The mesh according to any of claims 72-76, wherein the pores of the mesh are arranged in rows.

78. The mesh according to any of claims 72-77, wherein at least some of the pores overlap other pores within the mesh.

79. The mesh according to any of claims 72-78, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

80. The mesh according to any of claims 72-79, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

81. The mesh according to any of claims 72-80, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

82. A method for sewing a corner-lock stitch pattern, comprising (a) sewing a first upper thread and a first lower thread in a first pattern into a substrate material, the first pattern comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, then (b) sewing a second upper thread and a second lower thread in a

second pattern into the substrate material, the second pattern comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

83. The method according to claim 82, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and at least one of the overlapping rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

84. The method according to any of claims 82 or 83, wherein the substrate material comprises a fabric.

85. The method according to any of claims 82-85, wherein the substrate material comprises a biotextile.

86. The method according to any of claims 82, 83, or 85, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular matrix.

87. The method according to any of claims 82-85, wherein the substrate material comprises a hernia repair mesh.

88. The method according to any of claims 82, 83, or 87, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene.

89. The method according to any of claims 82-88, wherein the substrate material is biocompatible.

90. The method according to any of claims 82-89, wherein the substrate material is resorbable.

91. The method according to any of claims 82-90, wherein the first and second upper and lower threads comprise a biocompatible material.

92. The method according to claim 91, wherein the biocompatible material is resorbable.

93. The method according to any of claims 82-92, wherein at least the first upper and first lower threads are the same continuous thread.

94. The method according to any of claims 82-93, wherein the sewing comprises hand sewing.

95. The method according to any of claims 82-93, wherein the sewing comprises machine sewing.

96. The method according to any of claims 82-95, further comprising, (c) repeating steps (a) and (b) any number of times, thereby producing a mesh comprising a corner-lock stitch pattern within the substrate material.

97. The method according to claim 96, wherein the sewing of steps (a), (b), and (c) is substantially continuous.

98. The method according to claim 96 or 97, further comprising (d) isolating the mesh from the substrate material.

99. The method according to any of claims 96-98, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

100. The method according to any of claims 96-98, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

101. The method according to any of claims 96-98, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

102. The method according to any of claims 96-98, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.
103. The method according to any of claims 96-102, wherein the pores of the mesh are arranged in rows.
104. The method according to any of claims 96-103, wherein at least some of the pores overlap other pores within the mesh.
105. The method according to any of claims 96-104, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.
106. The method according to any of claims 96-105, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.
107. The method according to any of claims 96-106, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.
108. The method according to any of claims 82-107, wherein each upper thread comprises a chain stitch pattern.
109. The method according to any of claims 82-108, wherein each upper thread comprises a yarn.
110. The method according to claim 109, wherein the yarn is a monofilament yarn.
111. The method according to claim 109, wherein the yarn is a multifilament yarn.
112. The method according to any of claims 82-111, wherein the first and second upper and lower threads comprise a continuous filament.
113. The method according to any of claims 82-111, wherein the first and second upper and lower threads comprise a staple filament.
114. The method according to any of claims 82-111, wherein the first and second upper and lower threads comprise a wire.
115. The method according to any of claims 82-114, wherein each upper thread and each

lower thread comprises a denier of at least about 20-denier.

116. The method according to any of claims 82-115, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.

117. The method according to any of claims 82-116, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.

118. The method according to any of claims 82-117, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.

119. The method according to claim 83, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

120. The method according to claim 83, wherein the one or more polygonal rings comprise an irregular shape.

121. A substrate material, comprising a corner-lock stitch pattern produced according to the method of any of claims 82-120.

122. A substrate material, comprising a mesh comprising a corner-lock stitch produced according to the method of any of claims 82-97 or claims 99-120.

123. The substrate material according to claim 122, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

124. The substrate material according to claim 122, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

125. The substrate material according to claim 122, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

126. The substrate material according to claim 122, wherein the mesh comprises a plurality

of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

127. The substrate material according to any of claims 122-126, wherein the pores of the mesh are arranged in rows.

128. The substrate material according to any of claims 122-127, wherein at least some of the pores overlap other pores within the mesh.

129. The substrate material according to any of claims 122-128, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

130. The substrate material according to any of claims 122-129, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

131. The substrate material according to any of claims 122-130, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

132. A mesh produced according to the method of claim 98.

133. The mesh according to claim 132, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

134. The mesh according to claim 132, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

135. The mesh according to claim 132, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

136. The mesh according to claim 132, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

137. The mesh according to any of claims 132-136, wherein the pores of the mesh are arranged in rows.

138. The mesh according to any of claims 132-137, wherein at least some of the pores overlap other pores within the mesh.

139. The mesh according to any of claims 132-138, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

140. The mesh according to any of claims 132-139, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

141. The mesh according to any of claims 132-140, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

142. A method for sewing a corner-lock stitch pattern, comprising (a) sewing a first upper thread and a first lower thread in a first pattern into a substrate material, the first pattern comprising one or more straight lines, then (b) sewing a second upper thread and a second lower thread in a second pattern into the substrate material, the second pattern comprising a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one of the straight lines of the first pattern and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

143. The method according to claim 142, wherein at least one of the polygonal rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

144. The method according to any of claims 142 or 143, wherein the substrate material comprises a fabric.

145. The method according to any of claims 142-145, wherein the substrate material comprises a biotextile.

146. The method according to any of claims 142, 143, or 145, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular

matrix.

147. The method according to any of claims 142-145, wherein the substrate material comprises a hernia repair mesh.

148. The method according to any of claims 142, 143, or 147, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene.

149. The method according to any of claims 142-148, wherein the substrate material is biocompatible.

150. The method according to any of claims 142-149, wherein the substrate material is resorbable.

151. The method according to any of claims 142-150, wherein the first and second upper and lower threads comprise a biocompatible material.

152. The method according to claim 151, wherein the biocompatible material is resorbable.

153. The method according to any of claims 142-152, wherein at least the first upper and first lower threads are the same continuous thread.

154. The method according to any of claims 142-153, wherein the sewing comprises hand sewing.

155. The method according to any of claims 142-153, wherein the sewing comprises machine sewing.

156. The method according to any of claims 142-155, further comprising, (c) repeating steps (a) and (b) any number of times, thereby producing a mesh comprising a corner-lock stitch pattern within the substrate material.

157. The method according to claim 156, wherein the sewing of steps (a), (b), and (c) is substantially continuous.

158. The method according to claim 156 or 157, further comprising (d) isolating the mesh from the substrate material.

159. The method according to any of claims 156-158, wherein the mesh comprises a plurality

of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

160. The method according to any of claims 156-158, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

161. The method according to any of claims 156-158, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

162. The method according to any of claims 156-158, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

163. The method according to any of claims 156-162, wherein the pores of the mesh are arranged in rows.

164. The method according to any of claims 156-163, wherein at least some of the pores overlap other pores within the mesh.

165. The method according to any of claims 156-164, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

166. The method according to any of claims 156-165, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

167. The method according to any of claims 156-166, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

168. The method according to any of claims 142-167, wherein each upper thread comprises a chain stitch pattern.

169. The method according to any of claims 142-168, wherein each upper thread comprises a yarn.

170. The method according to claim 169, wherein the yarn is a monofilament yarn.
171. The method according to claim 169, wherein the yarn is a multifilament yarn.
172. The method according to any of claims 142-171, wherein the first and second upper and lower threads comprise a continuous filament.
173. The method according to any of claims 142-171, wherein the first and second upper and lower threads comprise a staple filament.
174. The method according to any of claims 142-171, wherein the first and second upper and lower threads comprise a wire.
175. The method according to any of claims 142-174, wherein each upper thread and each lower thread comprises a denier of at least about 20-denier.
176. The method according to any of claims 142-175, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.
177. The method according to any of claims 172-176, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.
178. The method according to any of claims 142-177, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.
179. The method according to claim 142 or 143, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.
180. The method according to claim 142 or 143, wherein the one or more polygonal rings comprise an irregular shape.
181. The method according to claim 142 or 143, wherein the one or more polygonal rings comprise a triangular.
182. A substrate material, comprising a corner-lock stitch pattern produced according to the method of any of claims 142-182.
183. A substrate material, comprising a mesh comprising a corner-lock stitch produced according to the method of any of claims 142-157 or claims 159-181.

184. The substrate material according to claim 183, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

185. The substrate material according to claim 183, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

186. The substrate material according to claim 183, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

187. The substrate material according to claim 183, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

188. The substrate material according to any of claims 183-187, wherein the pores of the mesh are arranged in rows.

189. The substrate material according to any of claims 183-188, wherein at least some of the pores overlap other pores within the mesh.

190. The substrate material according to any of claims 183-189, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

191. The substrate material according to any of claims 183-190, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

192. The substrate material according to any of claims 183-191, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

193. A mesh produced according to the method of claim 158.

194. The mesh according to claim 193, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination

thereof.

195. The mesh according to claim 193, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

196. The mesh according to claim 193, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

197. The mesh according to claim 193, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

198. The mesh according to any of claims 193-197, wherein the pores of the mesh are arranged in rows.

199. The mesh according to any of claims 193-198, wherein at least some of the pores overlap other pores within the mesh.

200. The mesh according to any of claims 193-199, wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

201. The mesh according to any of claims 193-200, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

202. The mesh according to any of claims 193-201, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

203. A corner-lock stitch pattern, comprising a first pattern of a first upper thread and a first lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread and a second lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch

pattern comprising at least one thread interlace point substantially at the vertex of each curve, angle, or curve and angle, and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

204. The corner lock stitch pattern according to claim 203, wherein the first pattern comprises a plurality of curves forming one or more circular rings, and the second pattern comprises a plurality of curves forming one or more circular rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising a thread interlace point substantially at the vertex of the overlapped curve of each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

205. The corner lock stitch pattern according to claim 203, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of overlapped angles from each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

206. The corner lock stitch pattern according to any of claims 203-205, wherein the first and second upper and lower threads comprise a biocompatible material.

207. The corner lock stitch pattern according to claim 206, wherein the biocompatible material is resorbable.

208. The corner lock stitch pattern according to any of claims 203-207, wherein at least the first upper and first lower threads are the same continuous thread.

209. The corner lock stitch pattern according to any of claims 203-208, wherein each upper thread comprises a chain stitch pattern.

210. The corner lock stitch pattern according to any of claims 203-209, wherein each upper thread comprises a yarn.
211. The corner lock stitch pattern according to claim 210, wherein the yarn is a monofilament yarn.
212. The corner lock stitch pattern according to claim 210, wherein the yarn is a multifilament yarn.
213. The corner lock stitch pattern according to any of claims 203-212, wherein the first and second upper and lower threads comprise a continuous filament.
214. The corner lock stitch pattern according to any of claims 203-212, wherein the first and second upper and lower threads comprise a staple filament.
215. The corner lock stitch pattern according to any of claims 203-212, wherein the first and second upper and lower threads comprise a wire.
216. The corner lock stitch pattern according to any of claims 203-215, wherein each upper thread and each lower thread comprises a denier of at least about 20-denier.
217. The corner lock stitch pattern according to any of claims 203-216, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.
218. The corner lock stitch pattern according to any of claims 203-217, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.
219. The corner lock stitch pattern according to any of claims 203-218, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.
220. The corner lock stitch pattern according to any of claims 205-219, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.
221. The corner lock stitch pattern according to any of claims 205-219, wherein the one or more polygonal rings comprise an irregular shape.
222. A corner-lock stitch pattern, comprising a first pattern of a first upper thread and a first

lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread and a second lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

223. The corner lock stitch pattern according to claim 222, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and at least one of the overlapping rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

224. The corner lock stitch pattern according to claim 222 or 223, wherein the first and second upper and lower threads comprise a biocompatible material.

225. The corner lock stitch pattern according to claim 224, wherein the biocompatible material is resorbable.

226. The corner lock stitch pattern according to any of claims 222-225, wherein at least the first upper and first lower threads are the same continuous thread.

227. The corner lock stitch pattern according to any of claims 222-226, wherein each upper thread comprises a chain stitch pattern.

228. The corner lock stitch pattern according to any of claims 222-227, wherein each upper thread comprises a yarn.

229. The corner lock stitch pattern according to claim 228, wherein the yarn is a monofilament yarn.

230. The corner lock stitch pattern according to claim 228, wherein the yarn is a multifilament yarn.
231. The corner lock stitch pattern according to any of claims 222-226, wherein the first and second upper and lower threads comprise a continuous filament.
232. The corner lock stitch pattern according to any of claims 222-226, wherein the first and second upper and lower threads comprise a staple filament.
233. The corner lock stitch pattern according to any of claims 222-226, wherein the first and second upper and lower threads comprise a wire.
234. The corner lock stitch pattern according to any of claims 222-233, wherein each upper thread and each lower thread comprises a denier of at least about 20-denier.
235. The corner lock stitch pattern according to any of claims 222-234, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.
236. The corner lock stitch pattern according to any of claims 222-235, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.
237. The corner lock stitch pattern according to any of claims 222-236, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.
238. The corner lock stitch pattern according to claim 223, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.
239. The corner lock stitch pattern according to claim 223, wherein the one or more polygonal rings comprise an irregular shape.
240. A corner-lock stitch pattern, comprising a first pattern of a first upper thread and a first lower thread comprising one or more straight lines, and a second pattern of a second upper thread and a second lower thread comprising a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one of the straight lines of the first pattern and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay

comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

241. The corner-lock stitch pattern according to claim 240, wherein at least one of the polygonal rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

242. The corner lock stitch pattern according to claim 240 or 241, wherein the first and second upper and lower threads comprise a biocompatible material.

243. The corner lock stitch pattern according to claim 242, wherein the biocompatible material is resorbable.

244. The corner lock stitch pattern according to any of claims 240-243, wherein at least the first upper and first lower threads are the same continuous thread.

245. The corner lock stitch pattern according to any of claims 240-244, wherein each upper thread comprises a chain stitch pattern.

246. The corner lock stitch pattern according to any of claims 240-245, wherein each upper thread comprises a yarn.

247. The corner lock stitch pattern according to claim 246, wherein the yarn is a monofilament yarn.

248. The corner lock stitch pattern according to claim 246, wherein the yarn is a multifilament yarn.

249. The corner lock stitch pattern according to any of claims 240-245, wherein the first and second upper and lower threads comprise a continuous filament.

250. The corner lock stitch pattern according to any of claims 240-245, wherein the first and second upper and lower threads comprise a staple filament.

251. The corner lock stitch pattern according to any of claims 240-245, wherein the first and second upper and lower threads comprise a wire.

252. The corner lock stitch pattern according to any of claims 240-251, wherein each upper

thread and each lower thread comprises a denier of at least about 20-denier.

253. The corner lock stitch pattern according to any of claims 240-252, wherein each upper thread and each lower thread comprises a denier of at least about 50-denier.

254. The corner lock stitch pattern according to any of claims 240-253, wherein each upper thread and each lower thread comprises a denier of at least about 100-denier.

255. The corner lock stitch pattern according to any of claims 240-254, wherein each upper thread and each lower thread comprises a denier of at least about 200-denier.

256. The corner lock stitch pattern according to any of claims 240-255, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

257. The corner lock stitch pattern according to any of claims 240-255, wherein the one or more polygonal rings comprise an irregular shape.

258. The corner lock stitch pattern according to any of claims 240-255, wherein the one or more polygonal rings comprise a triangular shape.

259. A substrate material, comprising a substrate material having a corner-lock stitch pattern comprising a first pattern of a first upper thread and a first lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread and a second lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of each curve, angle, or curve and angle, and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

260. The substrate material according to claim 259, wherein the first pattern comprises a plurality of curves forming one or more circular rings, and the second pattern comprises a

plurality of curves forming one or more circular rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising a thread interlace point substantially at the vertex of the overlapped curve of each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

261. The substrate material according to claim 249, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and each overlapping ring comprises a corner-lock stitch pattern comprising at least one thread interlace point substantially at the vertex of overlapped angles from each ring and two thread overlays proximal to each vertex, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

262. The substrate material according to any of claims 259-261, wherein the substrate material comprises a fabric.

263. The substrate material according to any of claims 259-261, wherein the substrate material comprises a biotextile.

264. The substrate material according to any of claims 259-261 or 263, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular matrix.

265. The substrate material according to any of claims 259-261, wherein the substrate material comprises a hernia repair mesh.

266. The substrate material according to any of claims 259-261 or 265, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene or polyethelylene.

267. The substrate material according to any of claims 279-286, wherein the substrate

material is biocompatible.

268. The substrate material according to any of claims 259-267, wherein the substrate material is resorbable.

269. The substrate material according to any of claims 259-268, wherein the corner-lock stitch pattern comprises a mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

270. The substrate material according to claim 269, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

271. The substrate material according to claim 269, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

272. The substrate material according to claim 269, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

273. The substrate material according to any of claims 269-272, wherein the pores of the mesh are arranged in rows.

274. The substrate material according to any of claims 269-273, wherein at least some of the pores overlap other pores within the mesh.

275. The substrate material according to any of claims 269-274 wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

276. The substrate material according to any of claims 269-275, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

277. The substrate material according to any of claims 269-276, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

278. The substrate material according to claim 261-277, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

279. The substrate material according to claim 261-277, wherein the one or more polygonal rings comprise an irregular shape.

280. A substrate material, comprising a substrate material having a corner-lock stitch pattern comprising a first pattern of a first upper thread and a first lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles, and a second pattern of a second upper thread and a second lower thread comprising one or more curves, one or more angles, or a combination of one or more curves and one or more angles; wherein at least one of the one or more curves or the one or more angles of the second pattern overlaps at least one of the one or more curves or the one or more angles of the first pattern, and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

281. The substrate material pattern according to claim 280, wherein the first pattern comprises a plurality of angles forming one or more polygonal rings, and the second pattern comprises a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one ring of the first pattern, and at least one of the overlapping rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

282. The substrate material according to claim 280 or 281, wherein the substrate material comprises a fabric.

283. The substrate material according to claim 280 or 281, wherein the substrate material comprises a biotextile.

284. The substrate material according to any of claims 280, 281 or 283, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular matrix.

285. The substrate material according to any of claims 280-284, wherein the substrate material comprises a hernia repair mesh.

286. The substrate material according to any of claims 280-285, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene or polyethylene.

287. The substrate material according to any of claims 280-286, wherein the substrate material is biocompatible.

288. The substrate material according to any of claims 280-287, wherein the substrate material is resorbable.

289. The substrate material according to any of claims 280-288, wherein the corner-lock stitch pattern comprises a mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.

290. The substrate material according to claim 289, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.

291. The substrate material according to claim 289, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.

292. The substrate material according to claim 289, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.

293. The substrate material according to any of claims 289-292, wherein the pores of the mesh are arranged in rows.

294. The substrate material according to any of claims 289-293, wherein at least some of the pores overlap other pores within the mesh.

295. The substrate material according to any of claims 289-294 wherein at least some of the

pores comprise one or more cross-stitches that span at least one dimension of the pore.

296. The substrate material according to any of claims 289-295, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

297. The substrate material according to any of claims 289-296, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

298. The substrate material according to any of claims 281-287, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

299. The substrate material according to any of claims 281-287, wherein the one or more polygonal rings comprise an irregular shape.

300. A substrate material, comprising a substrate material having a corner-lock stitch pattern comprising a first pattern of a first upper thread and a first lower thread comprising one or more straight lines, and a second pattern of a second upper thread and a second lower thread comprising a plurality of angles forming one or more polygonal rings, wherein at least one ring of the second pattern overlaps at least one of the straight lines of the first pattern and each overlap comprises a corner-lock stitch pattern comprising one or more thread interlace points and two or more thread overlays, each overlay comprising the second upper thread and second lower thread enveloping the first upper thread and first lower thread.

301. The substrate material according to claim 300, wherein at least one of the polygonal rings comprises a corner-lock stitch pattern comprising more than one thread interlace point.

302. The substrate material according to claim 300 or 301, wherein the substrate material comprises a fabric.

303. The substrate material according to claim 300 or 301, wherein the substrate material comprises a biotextile.

304. The substrate material according to any of claims 300, 301 or 303, wherein the substrate material comprises a biotextile and the biotextile comprises a tissue scaffold comprising an extracellular matrix.

305. The substrate material according to any of claims 300-304, wherein the substrate material comprises a hernia repair mesh.
306. The substrate material according to any of claims 300-305, wherein the substrate material comprises a hernia repair mesh and the hernia repair mesh comprises polypropylene.
307. The substrate material according to any of claims 300-306, wherein the substrate material is biocompatible.
308. The substrate material according to any of claims 300-307, wherein the substrate material is resorbable.
309. The substrate material according to any of claims 300-308, wherein the corner-lock stitch pattern comprises a mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a diamond shape, a square shape, a parallelogram shape, a rhomboid shape, or a combination thereof.
310. The substrate material according to claim 309, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially a hexagonal shape.
311. The substrate material according to claim 309, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and the pores have substantially a circular shape, an elliptical shape, a round shape, or a combination thereof.
312. The substrate material according to claim 309, wherein the mesh comprises a plurality of pores between the corner-lock stitch pattern, and at least some of the pores have substantially an octagonal shape.
313. The substrate material according to any of claims 309-312, wherein the pores of the mesh are arranged in rows.
314. The substrate material according to any of claims 289-293, wherein at least some of the pores overlap other pores within the mesh.
315. The substrate material according to any of claims 309-314 wherein at least some of the pores comprise one or more cross-stitches that span at least one dimension of the pore.

316. The substrate material according to any of claims 309-315, wherein the pores of the mesh substantially resist puncture-induced deformation of the pores.

317. The substrate material according to any of claims 309-316, wherein the pores of the mesh substantially resist tension-induced deformation of the pores.

318. The substrate material according to any of claims 300-317, wherein the one or more polygonal rings comprise substantially a diamond, square, rhomboid, rectangular, or parallelogram shape.

319. The substrate material according to any of claims 300-317, wherein the one or more polygonal rings comprise an irregular shape.

320. The substrate material according to any of claims 300-317, wherein the one or more polygonal rings comprise a triangular shape.

FIG. 1A

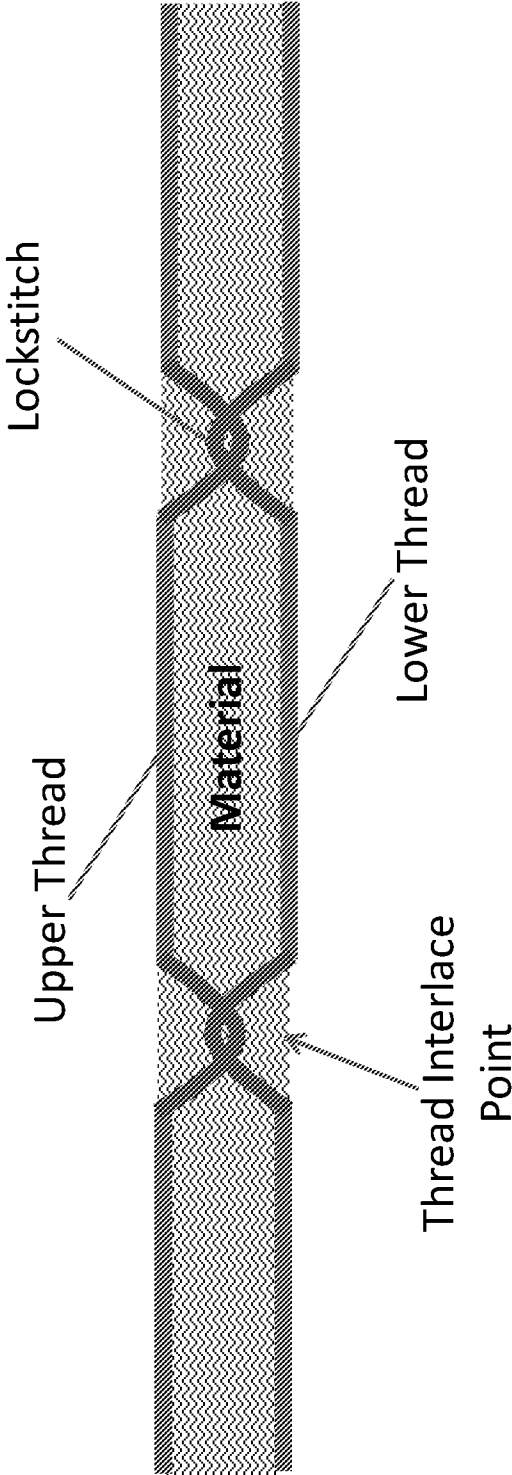
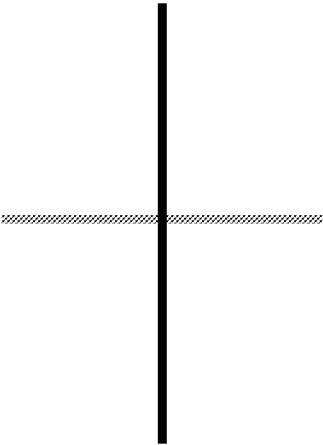


FIG. 1B



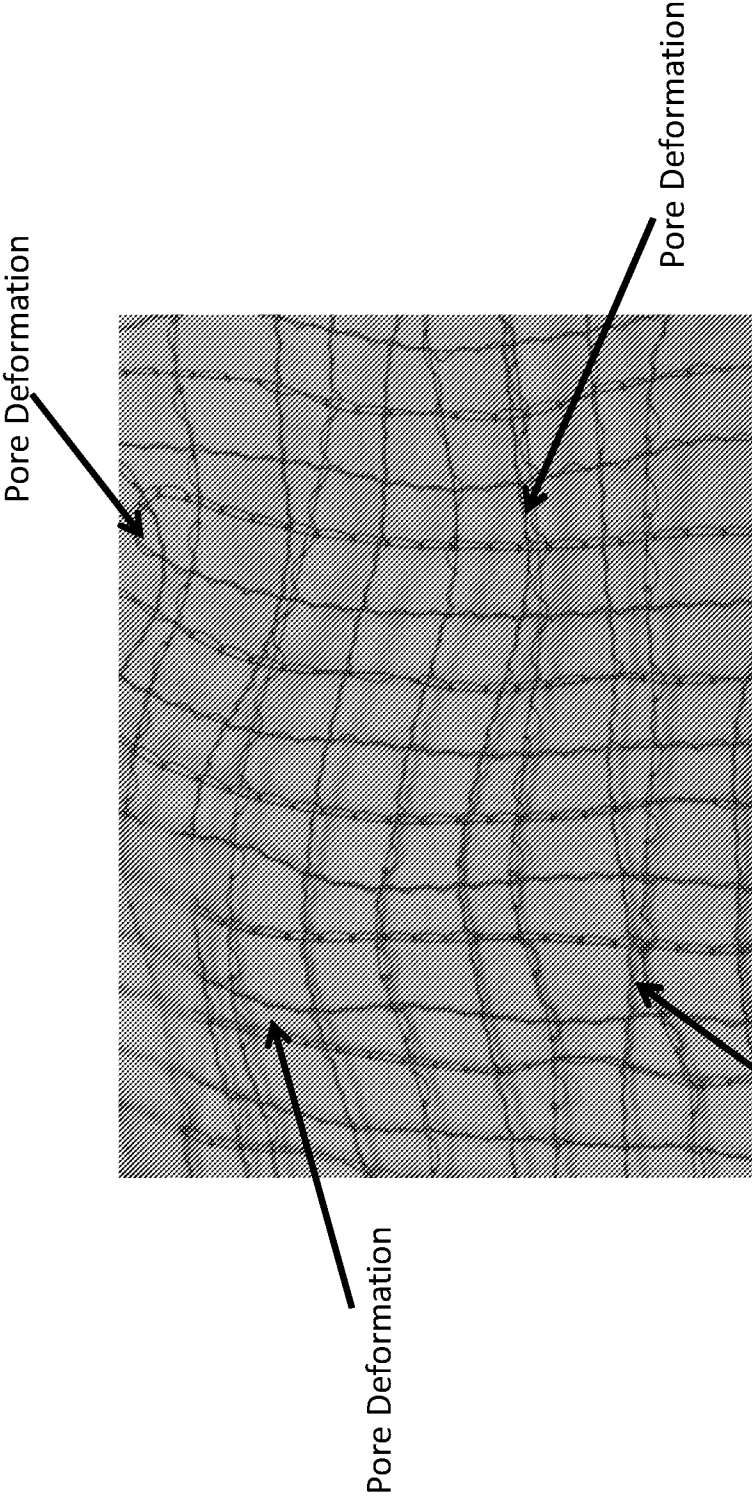


FIG. 2

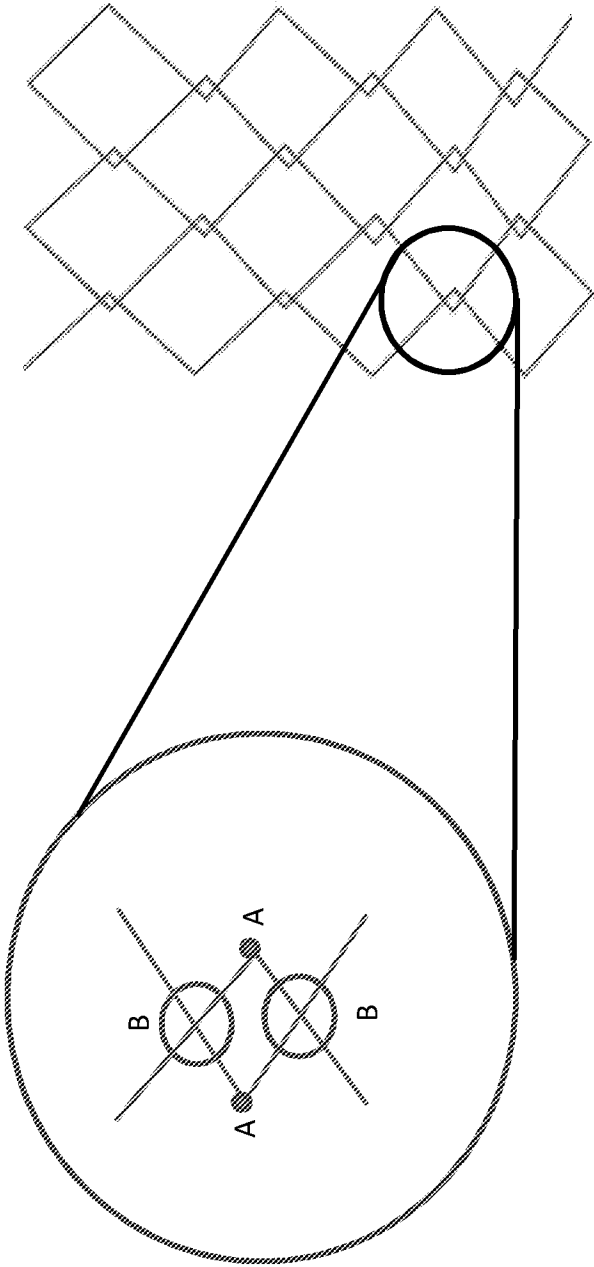


FIG. 3

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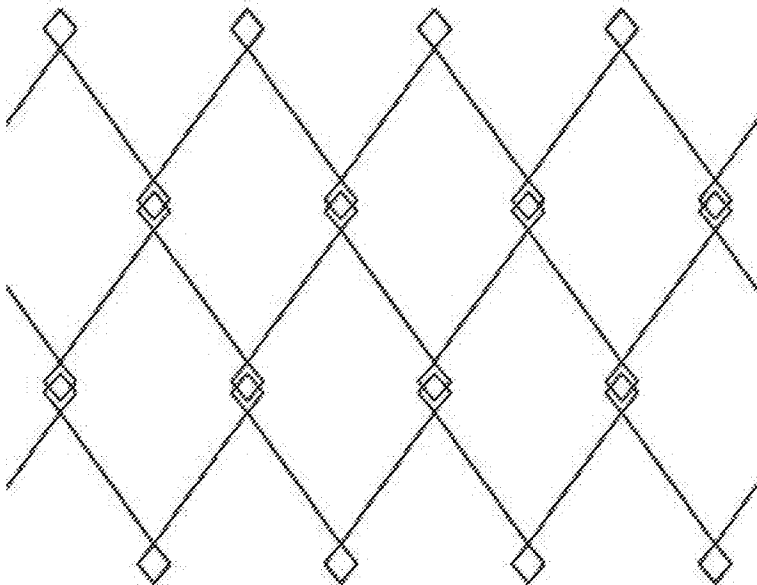


FIG. 4B

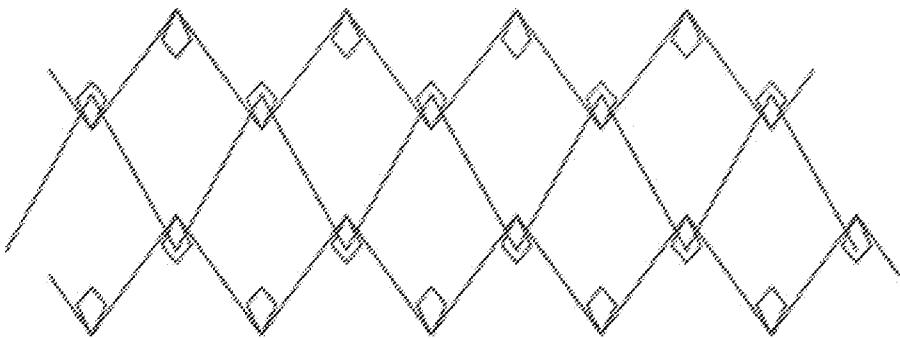


FIG. 4A

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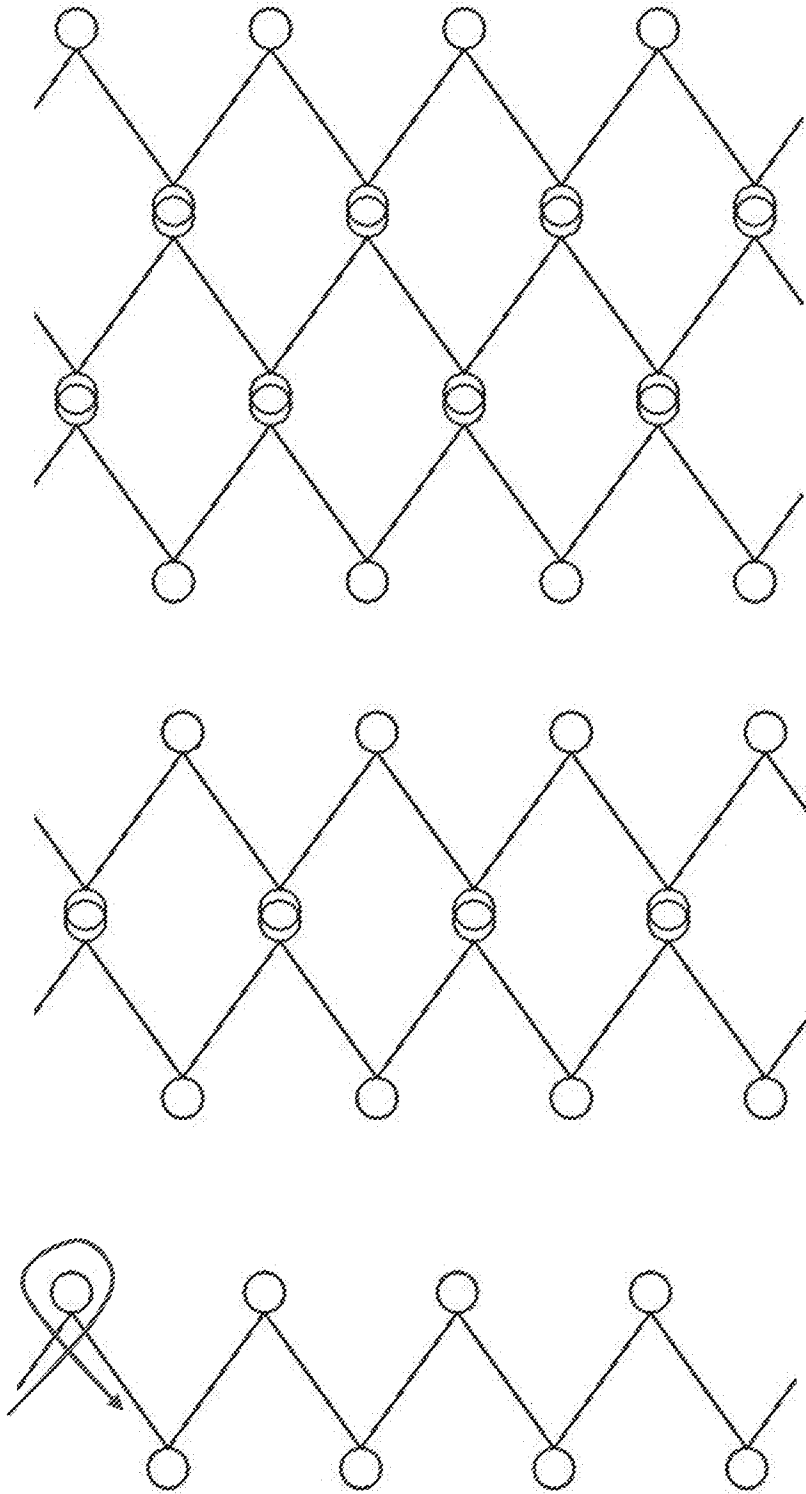


FIG. 4C

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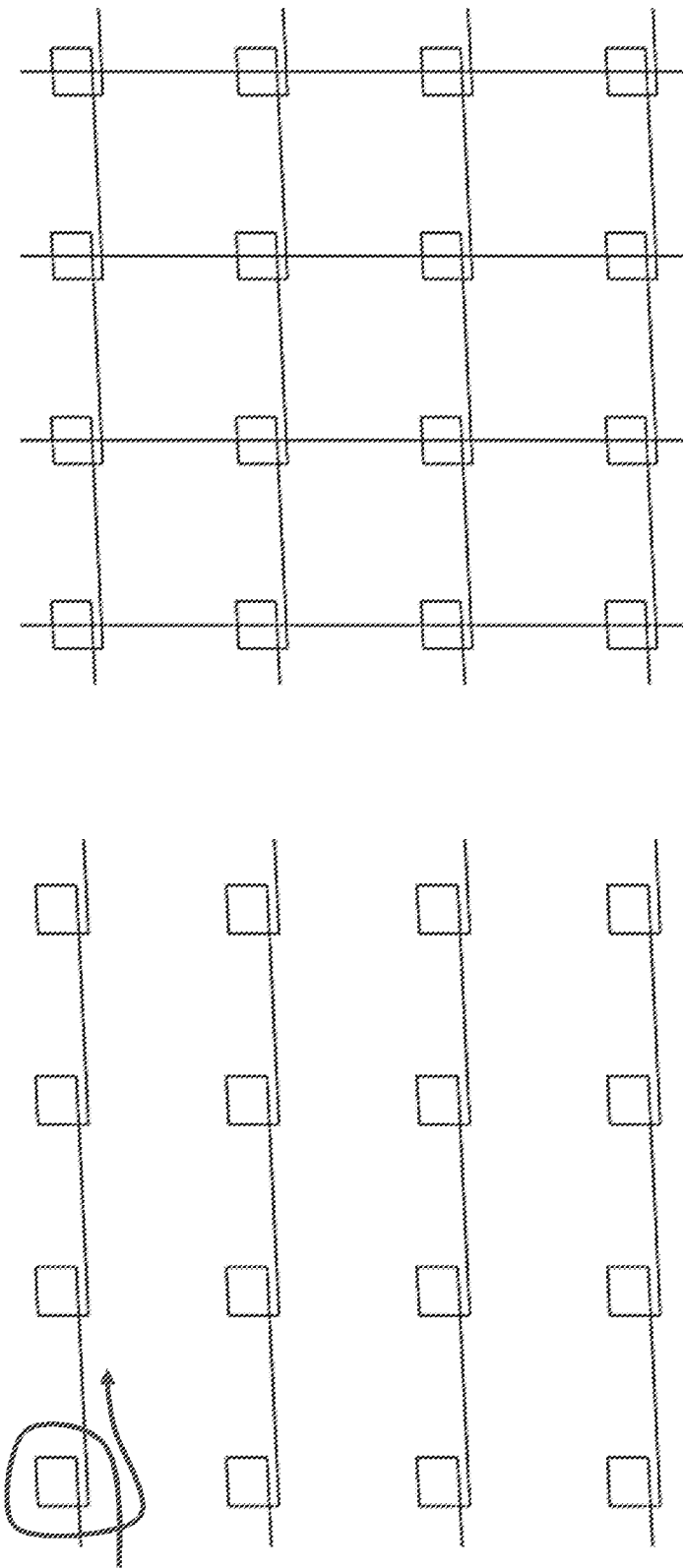


FIG. 5A

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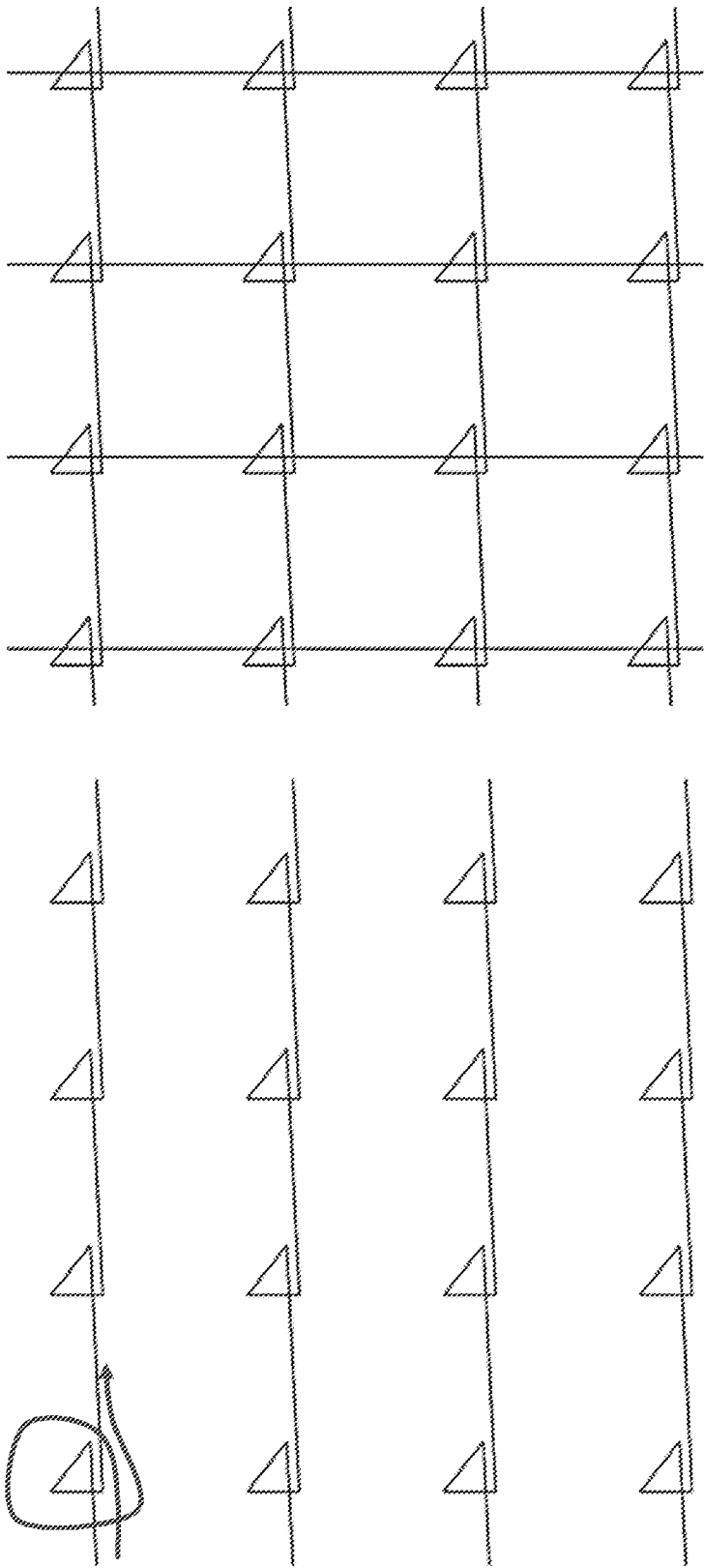


FIG. 5B

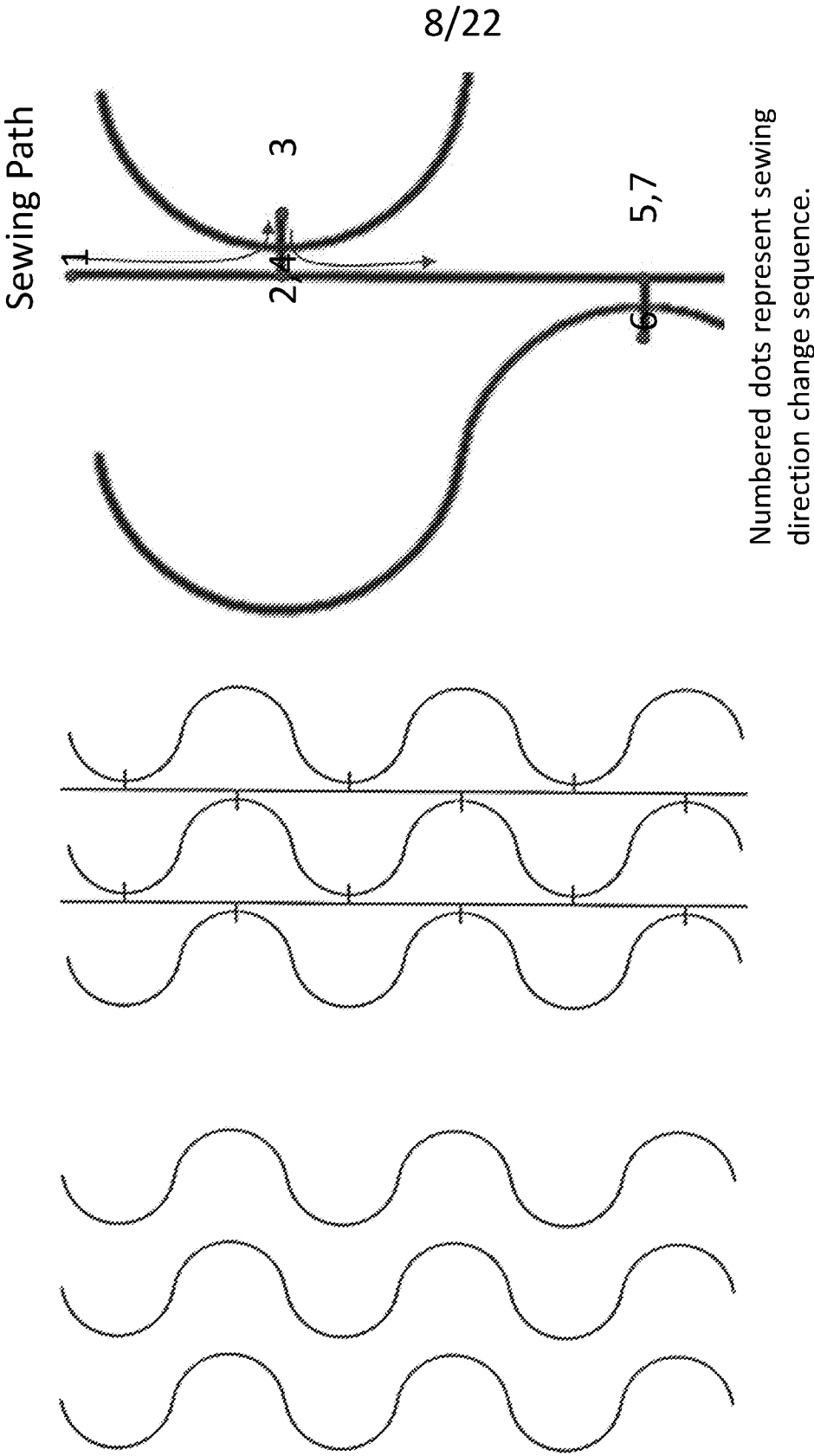


FIG. 5C

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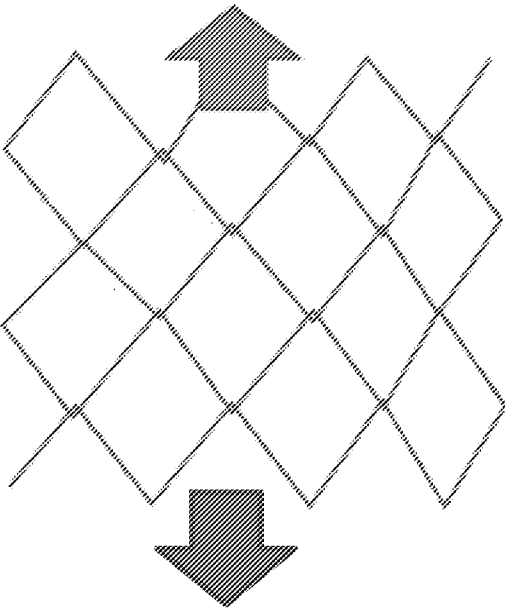


FIG. 6

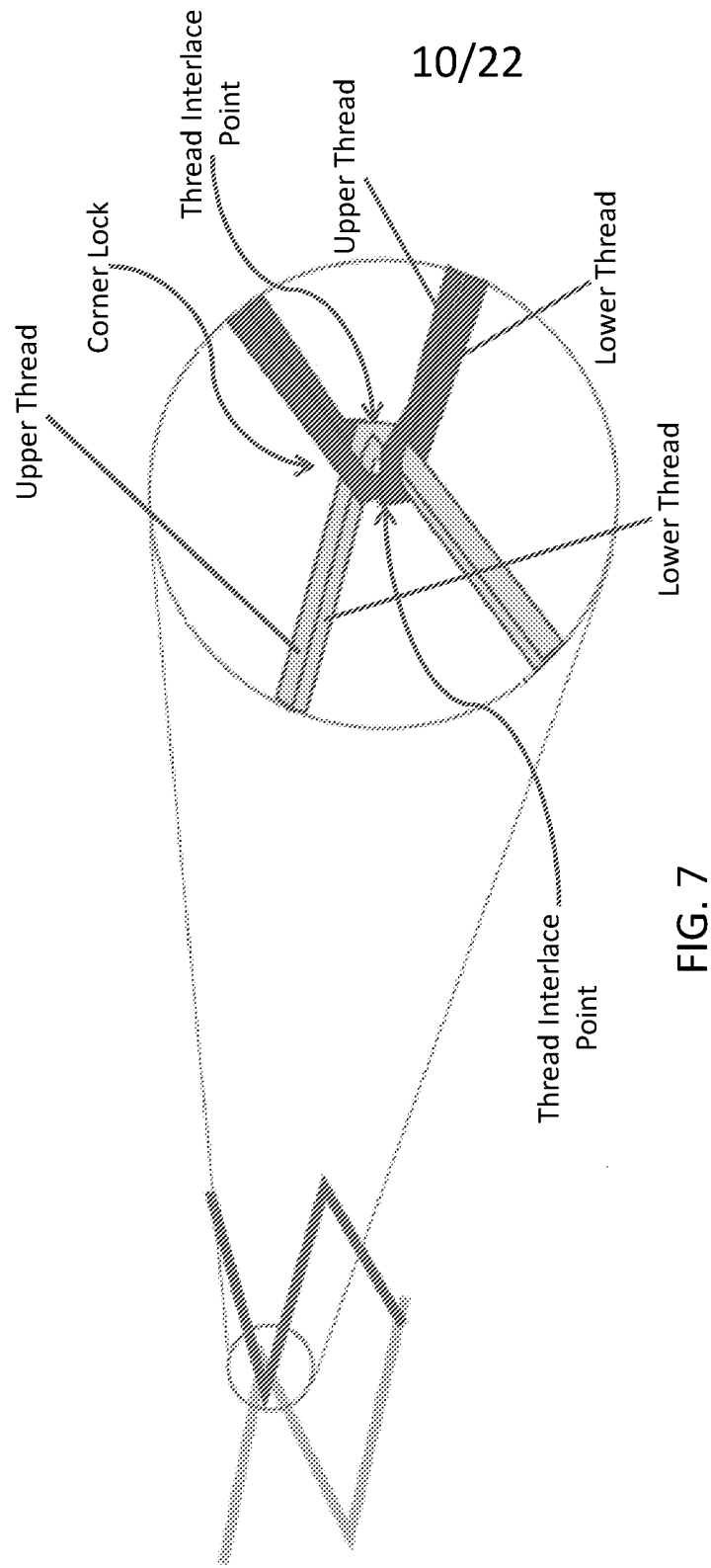


FIG. 7

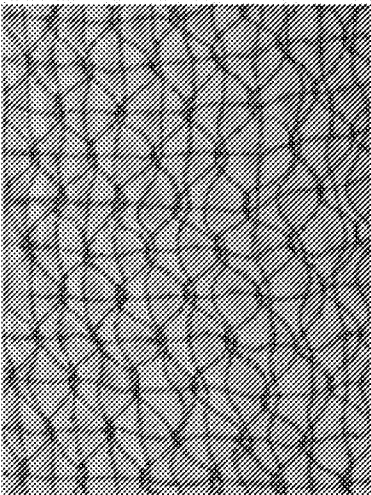


FIG. 8C

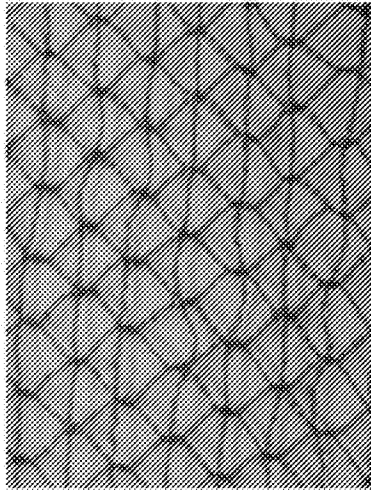


FIG. 8B

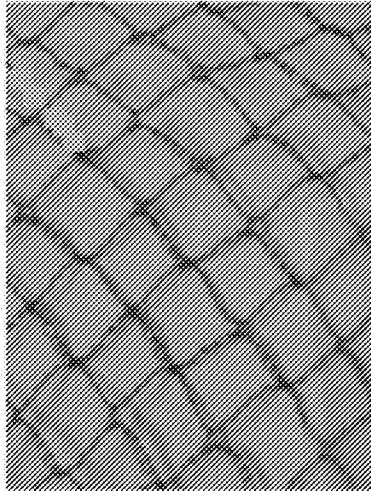


FIG. 8A

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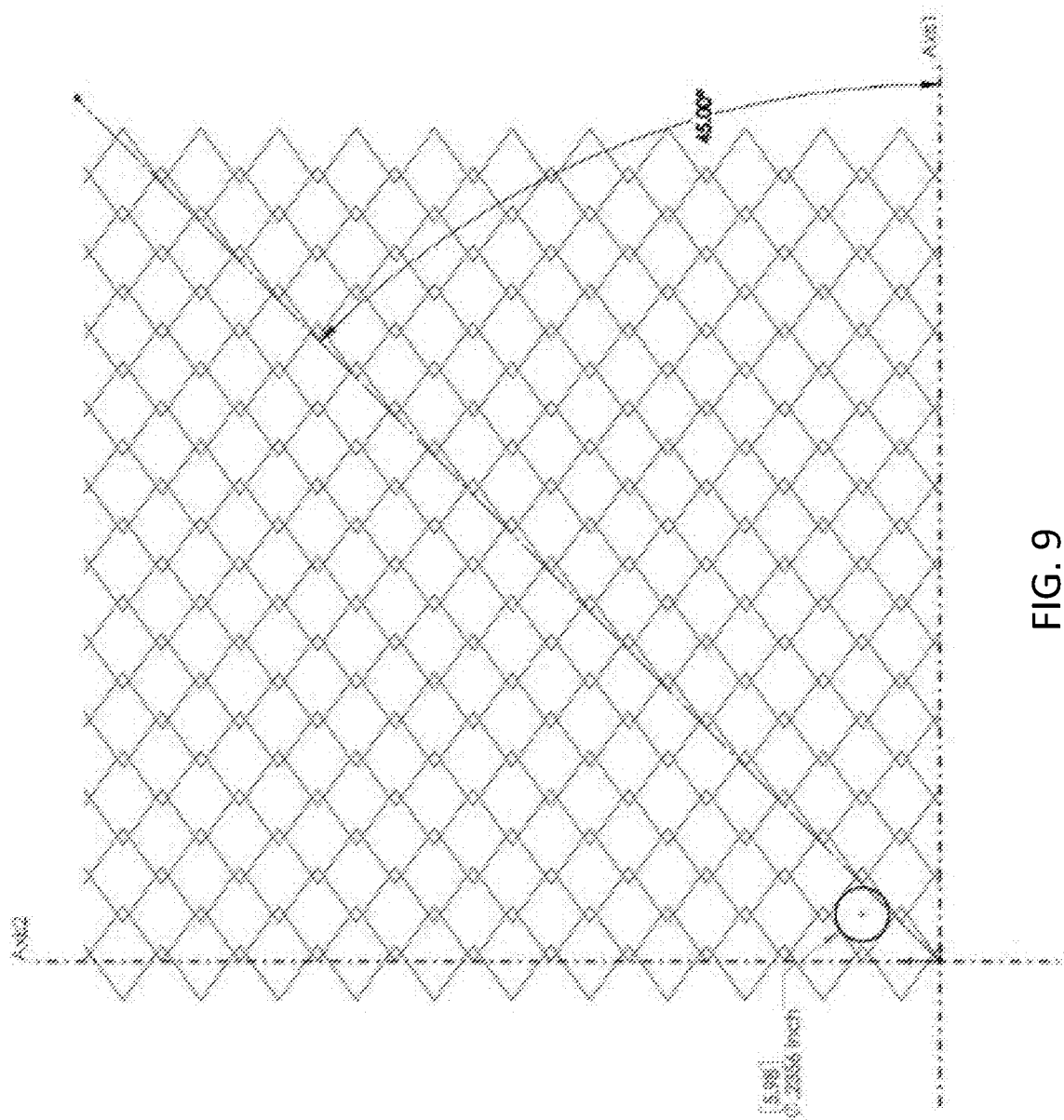


FIG. 9

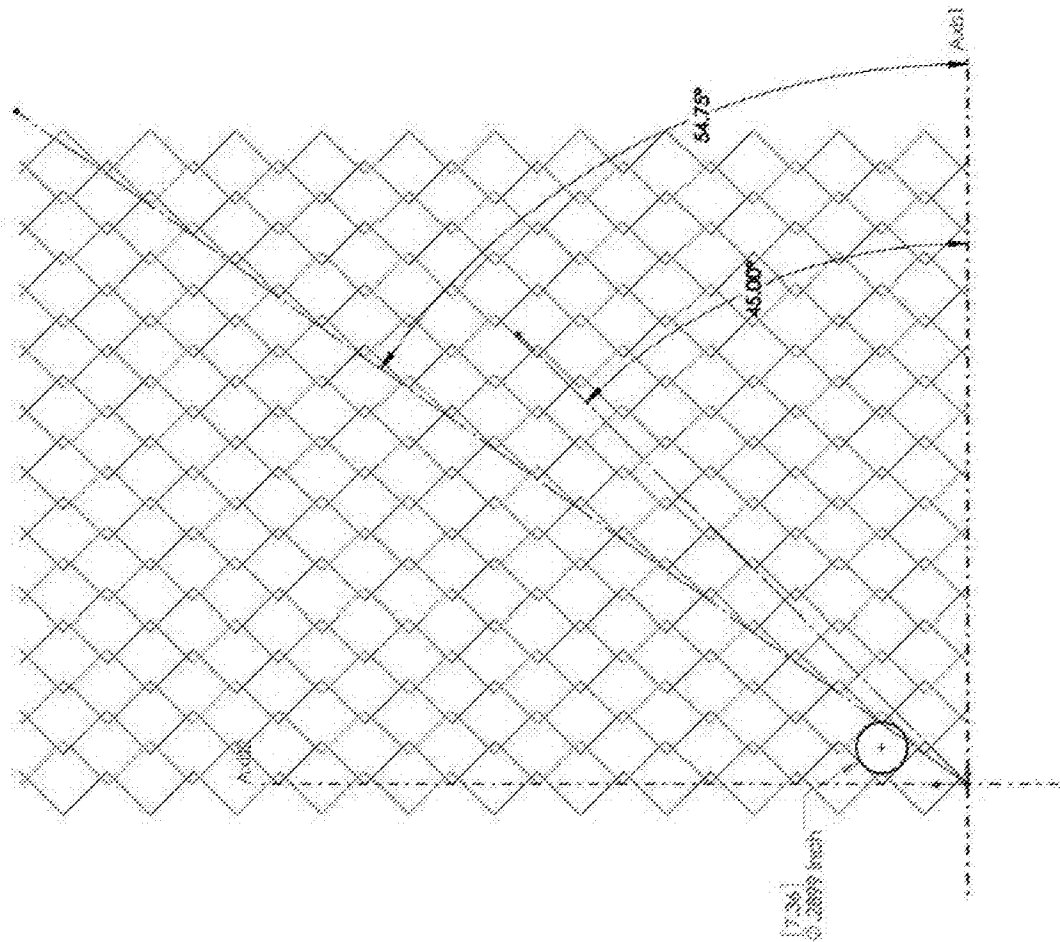


FIG. 10

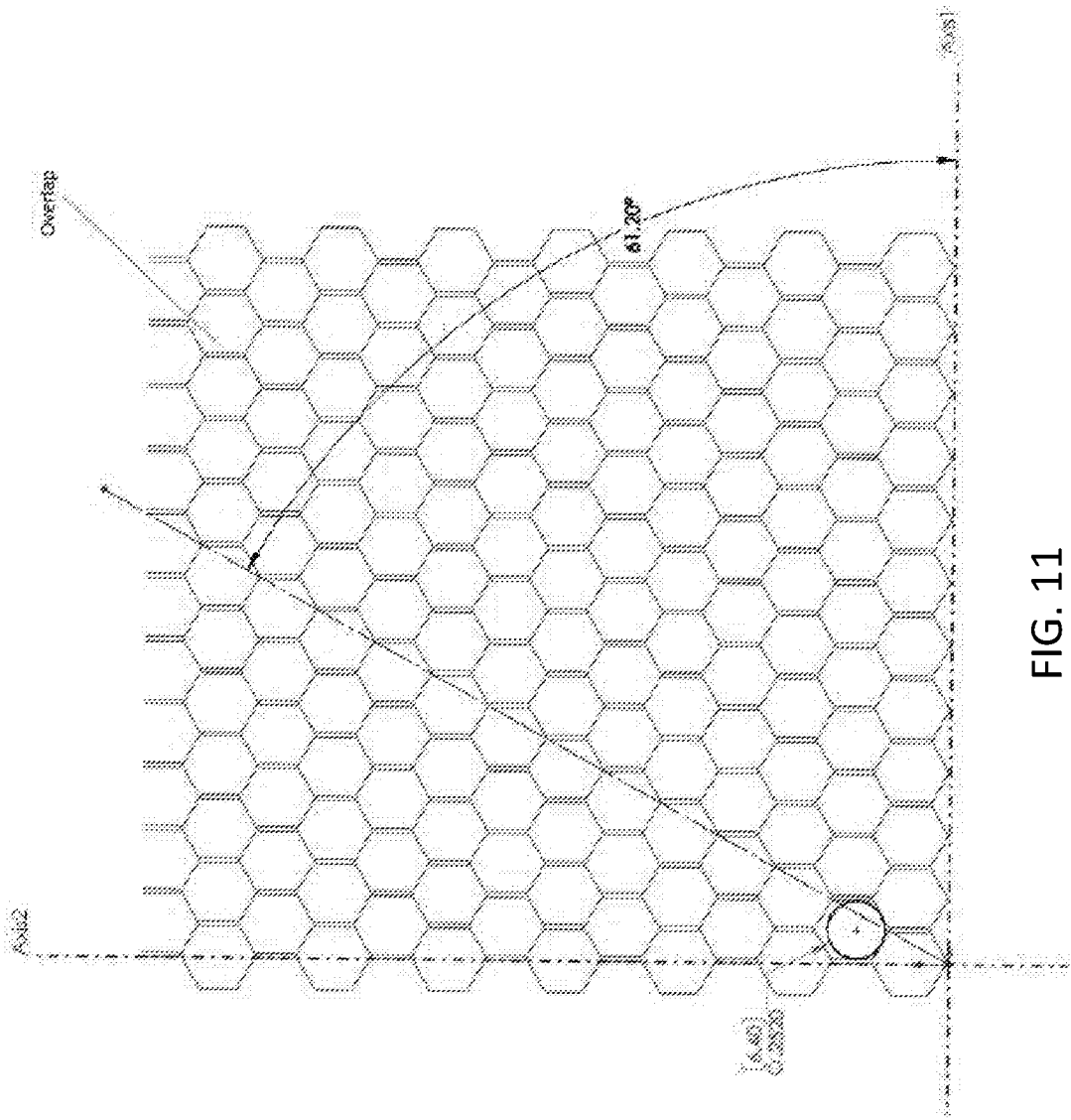


FIG. 11

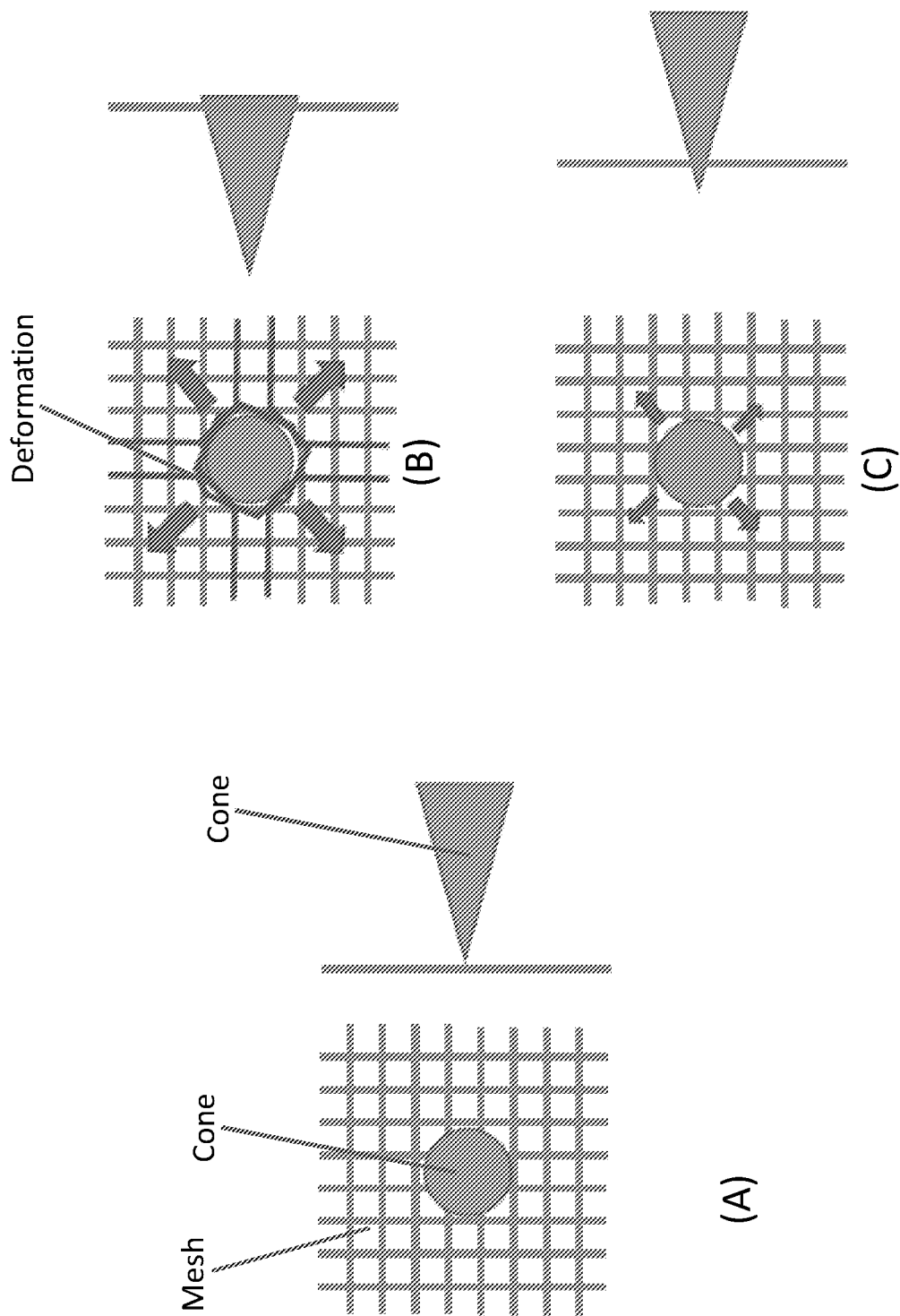


FIG. 12

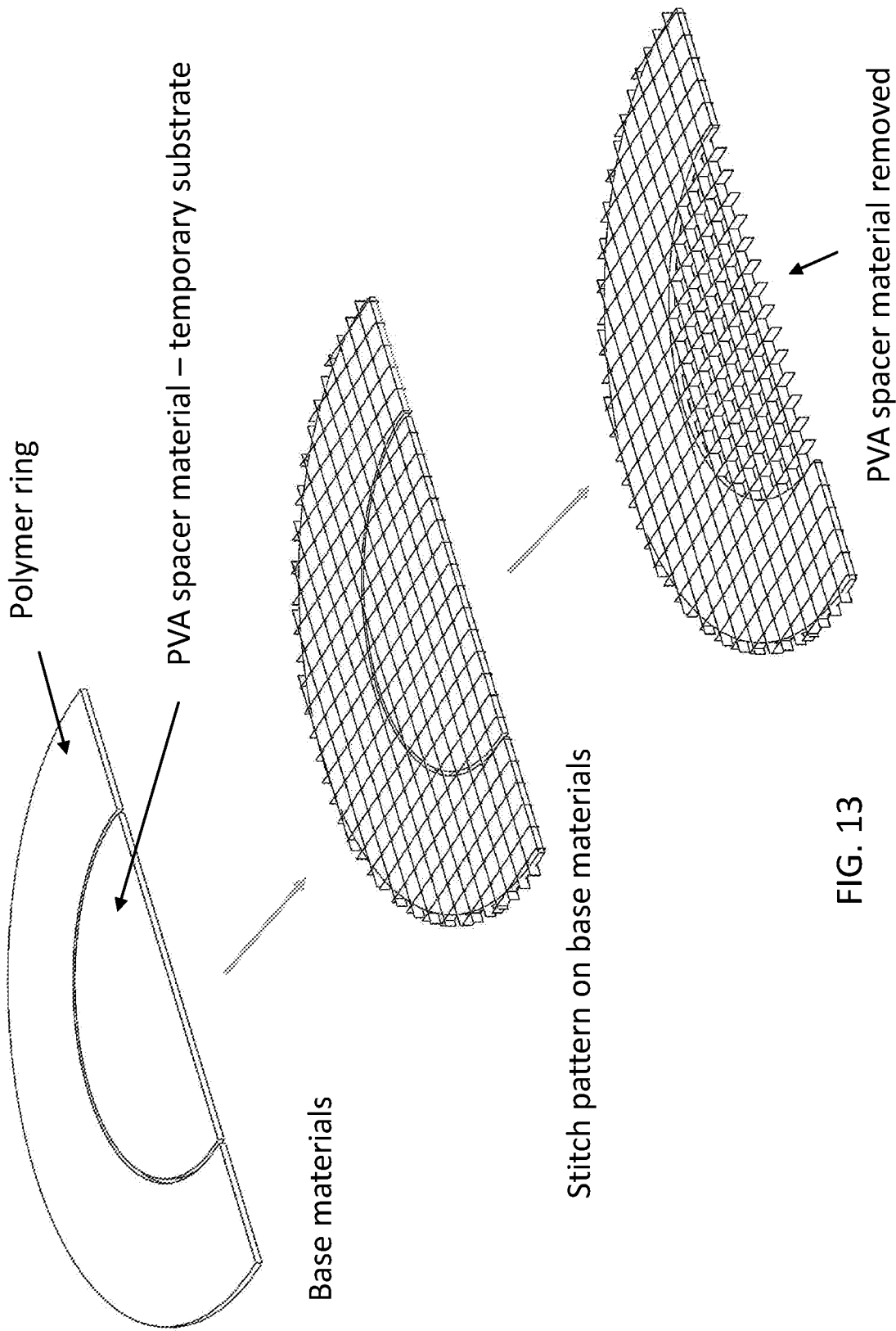


FIG. 13

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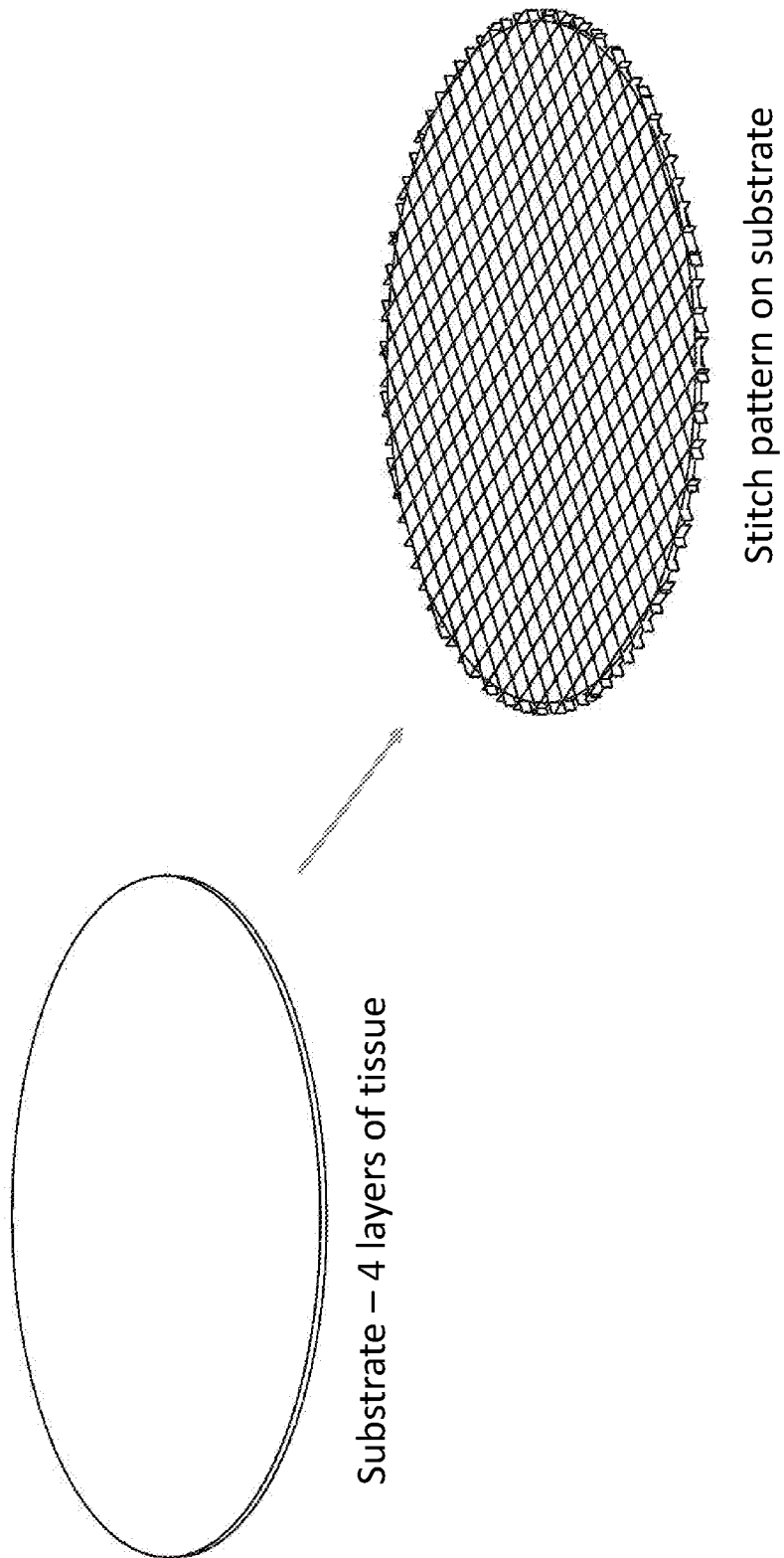
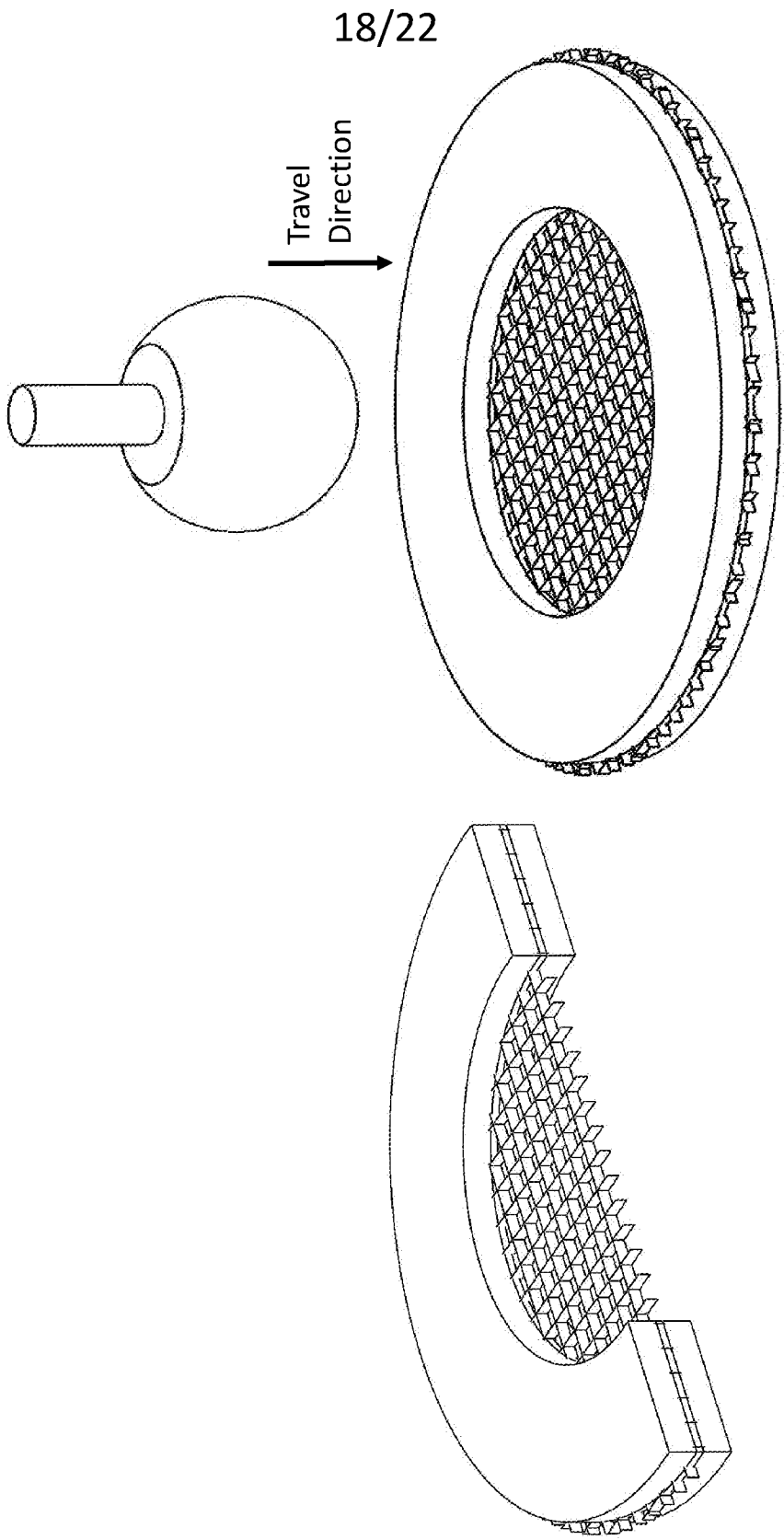


FIG. 14



Clamped Test Sample with Ball

Test Sample in Ring Clamp – Section View

FIG. 15

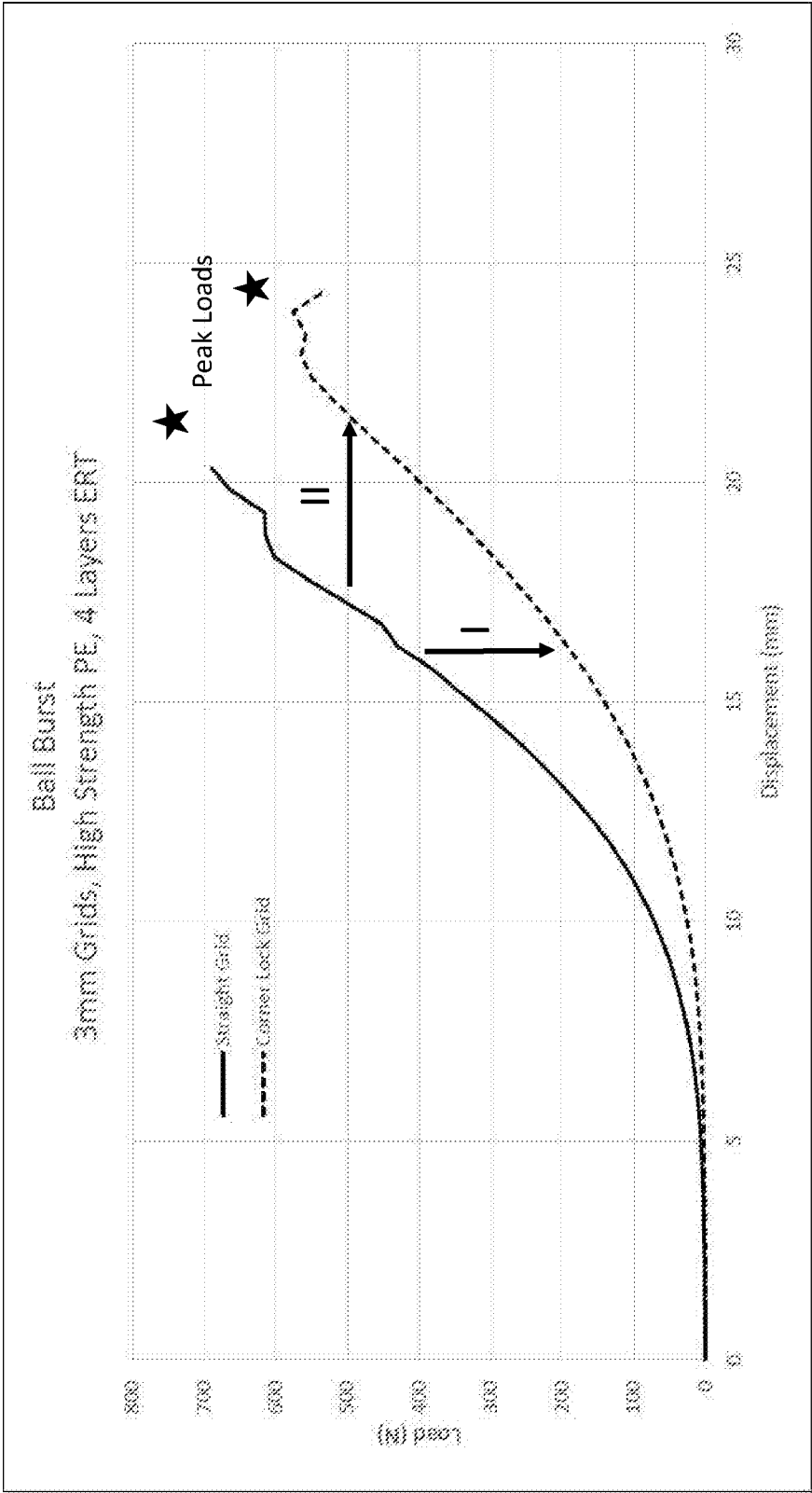


FIG. 16

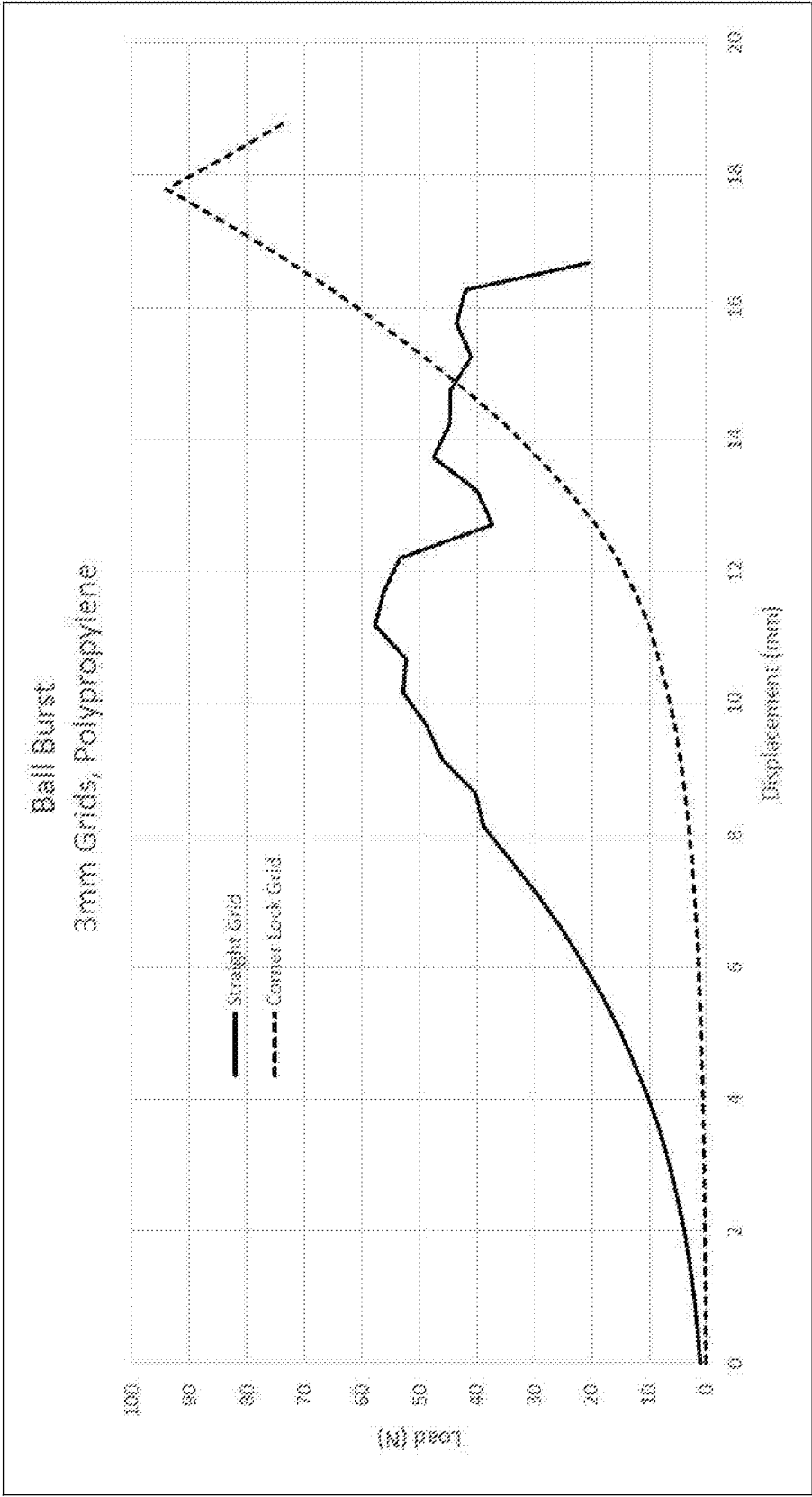


FIG. 17

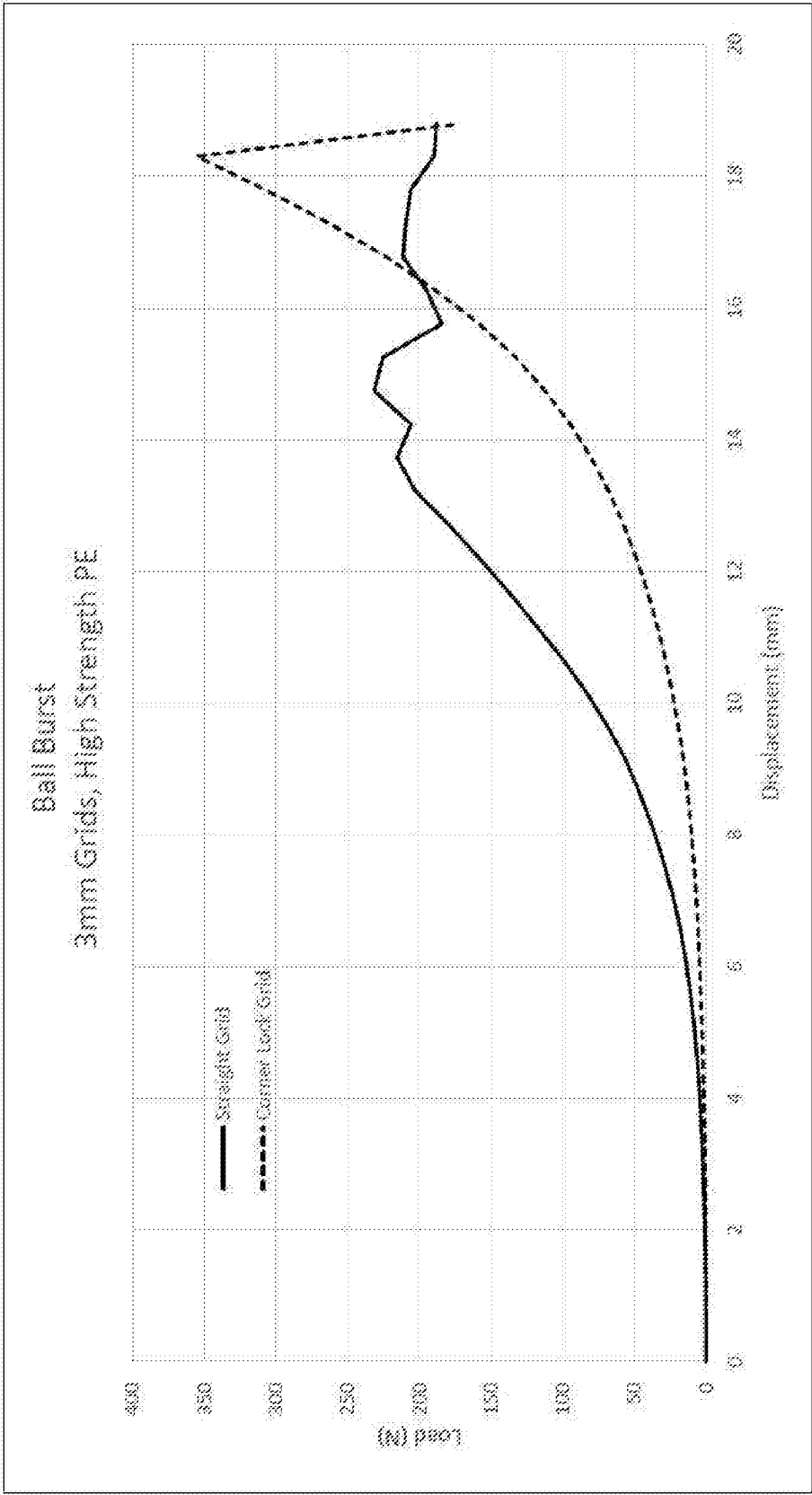


FIG. 18

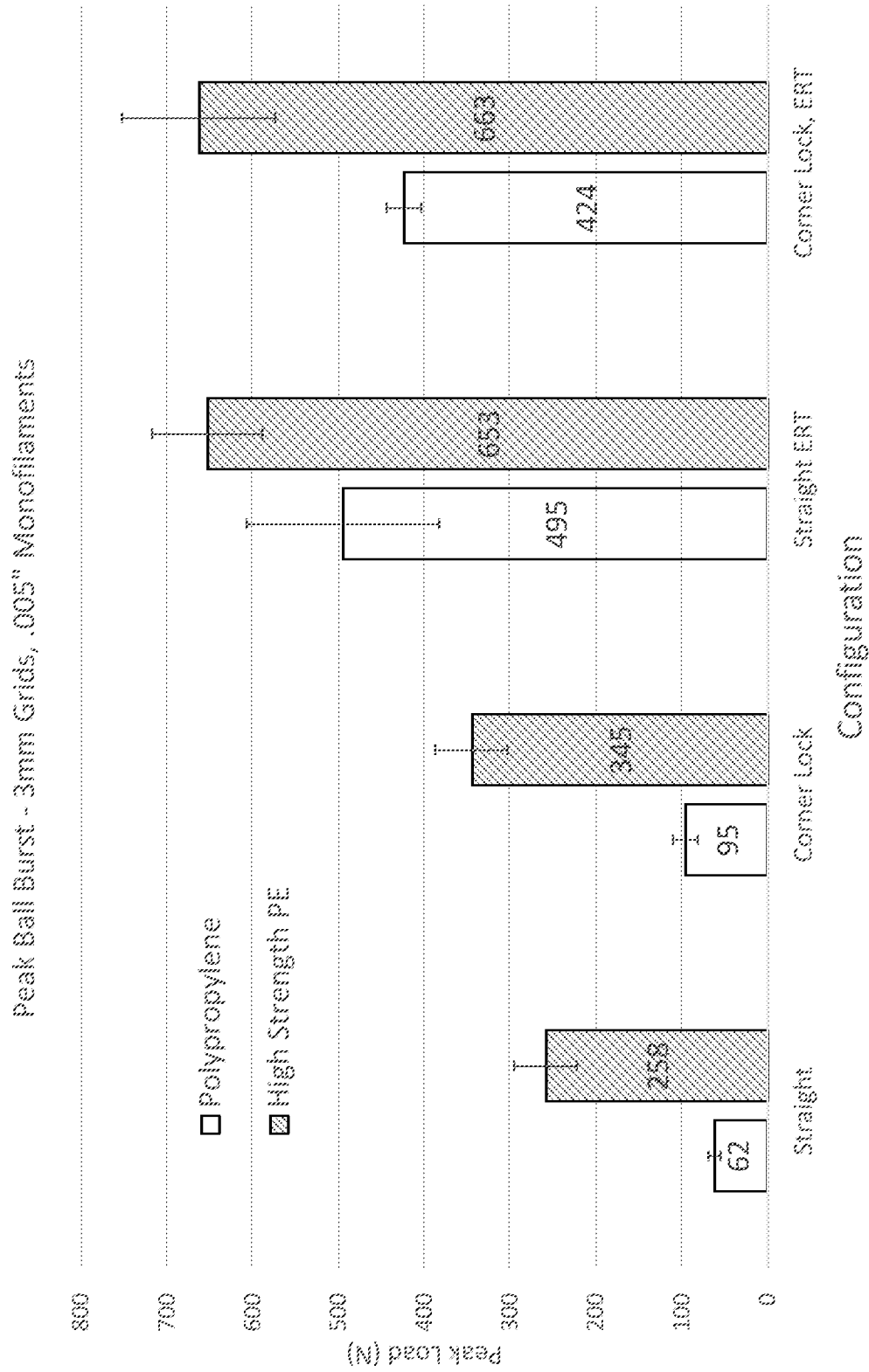


FIG. 19

INTERNATIONAL SEARCH REPORT

International application No
PCT/US2016/039984

A. CLASSIFICATION OF SUBJECT MATTER
INV. D05B1/12 A61F2/00
ADD.

According to International Patent Classification (IPC) or to both national classification and IPC

B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)
D05B A61F

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

EPO-Internal

C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	DE 103 12 674 A1 (MIKASA CORP [JP]) 23 October 2003 (2003-10-23) paragraph [0032] - paragraph [0076]; figures 1-10	1-320
A	----- WO 00/57812 A1 (ETHICON INC [US]) 5 October 2000 (2000-10-05) page 3, line 26 - page 9, line 16; figures 1-2	1-320
A	----- WO 03/094781 A1 (GFE MEDIZINTECHNIK GMBH [DE]; FRICKE HELMUT [DE]; BUTTSTAEDT JOHANNES) 20 November 2003 (2003-11-20) page 6, line 24 - page 10, line 2; figures 1-6	1-320
	----- -/-	



Further documents are listed in the continuation of Box C.



See patent family annex.

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"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

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"&" document member of the same patent family

Date of the actual completion of the international search

13 September 2016

Date of mailing of the international search report

27/09/2016

Name and mailing address of the ISA/

European Patent Office, P.B. 5818 Patentlaan 2
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Fax: (+31-70) 340-3016

Authorized officer

Herry-Martin, D

INTERNATIONAL SEARCH REPORT

International application No

PCT/US2016/039984

C(Continuation). DOCUMENTS CONSIDERED TO BE RELEVANT		
Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	RU 2 524 196 C1 (000 LINTEKS [RU]; EGIEV VALERIJ NIKOLAEVICH [RU]) 27 July 2014 (2014-07-27) the whole document -----	1-320

INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No

PCT/US2016/039984

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